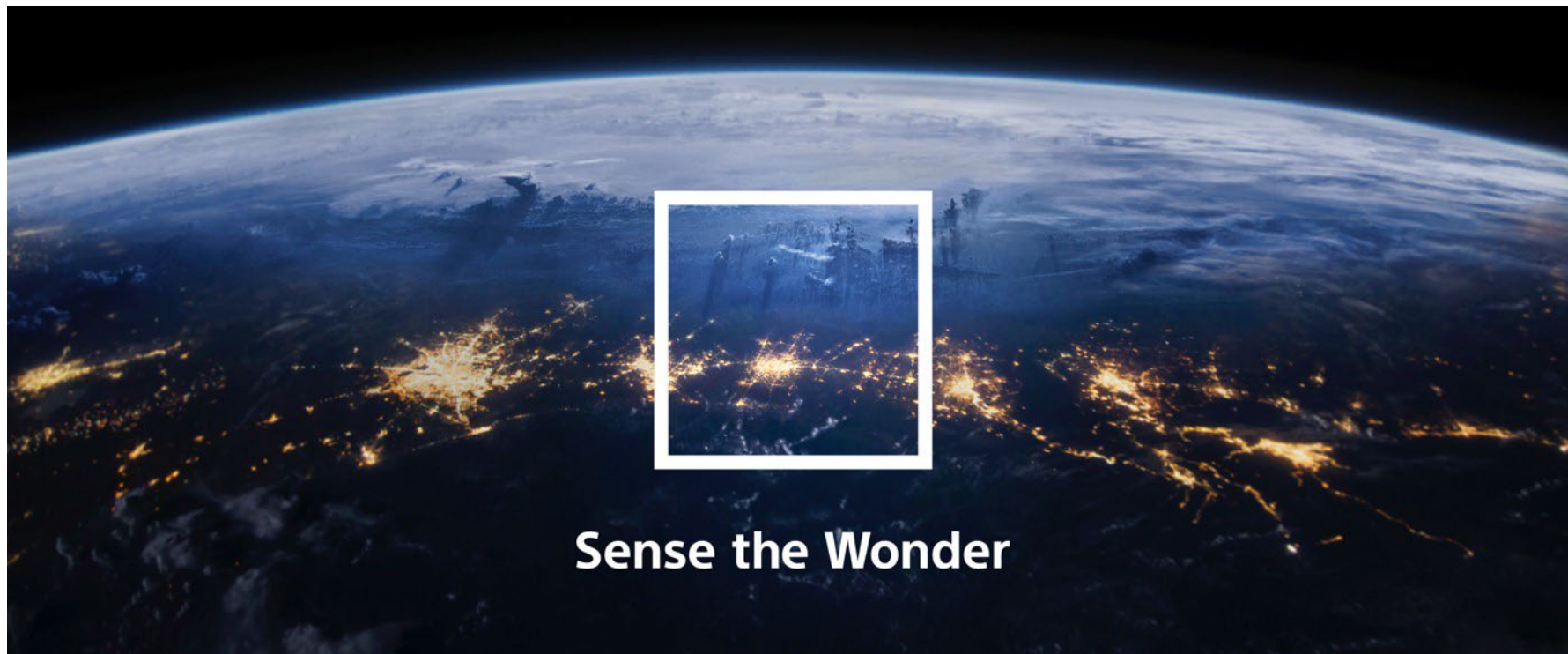


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Sense the Wonder

Recent advances in SPAD sensor technology: Pixel size shrinking and PDE enhancement

**4th June, 2024. International SPAD sensor workshop
Jun Ogi, Sony Semiconductor Solutions Corporation**

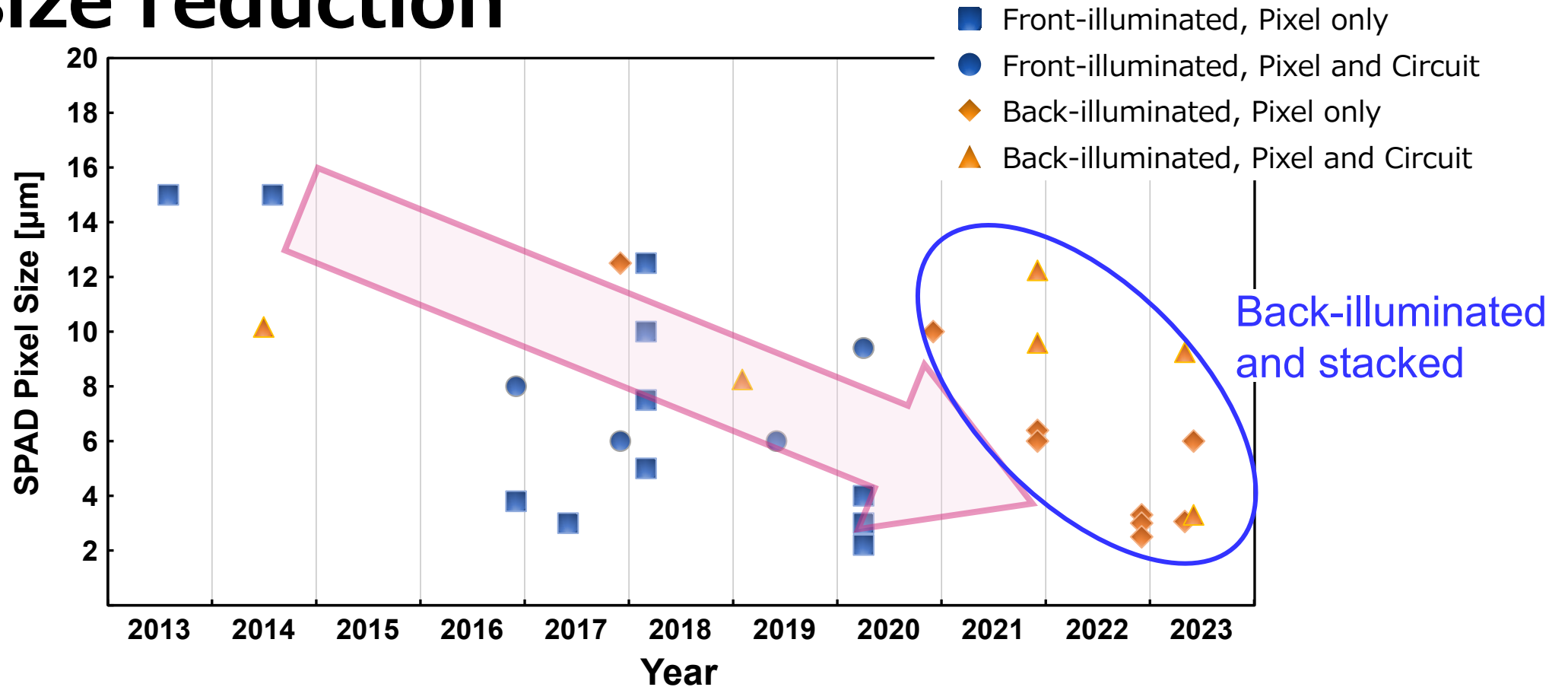
Outline

- 1. Pixel size reduction in SPAD sensor development**
- 2. Pixel size reduction to 2.5 μm**
- 3. PDE enhancement for near infrared**
- 4. High-resolution photon-counting image sensor**
- 5. Challenge of reducing pixel size via new structure**
- 6. Summary**

Outline

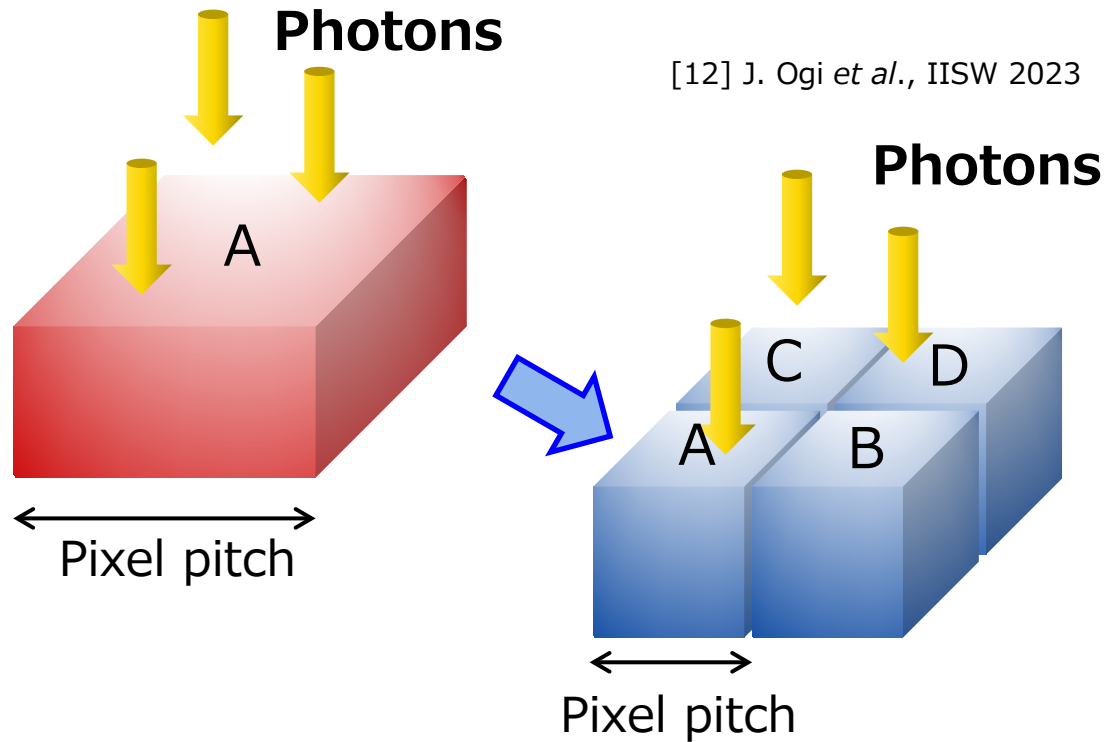
- 1. Pixel size reduction in SPAD sensor development**
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Pixel size reduction



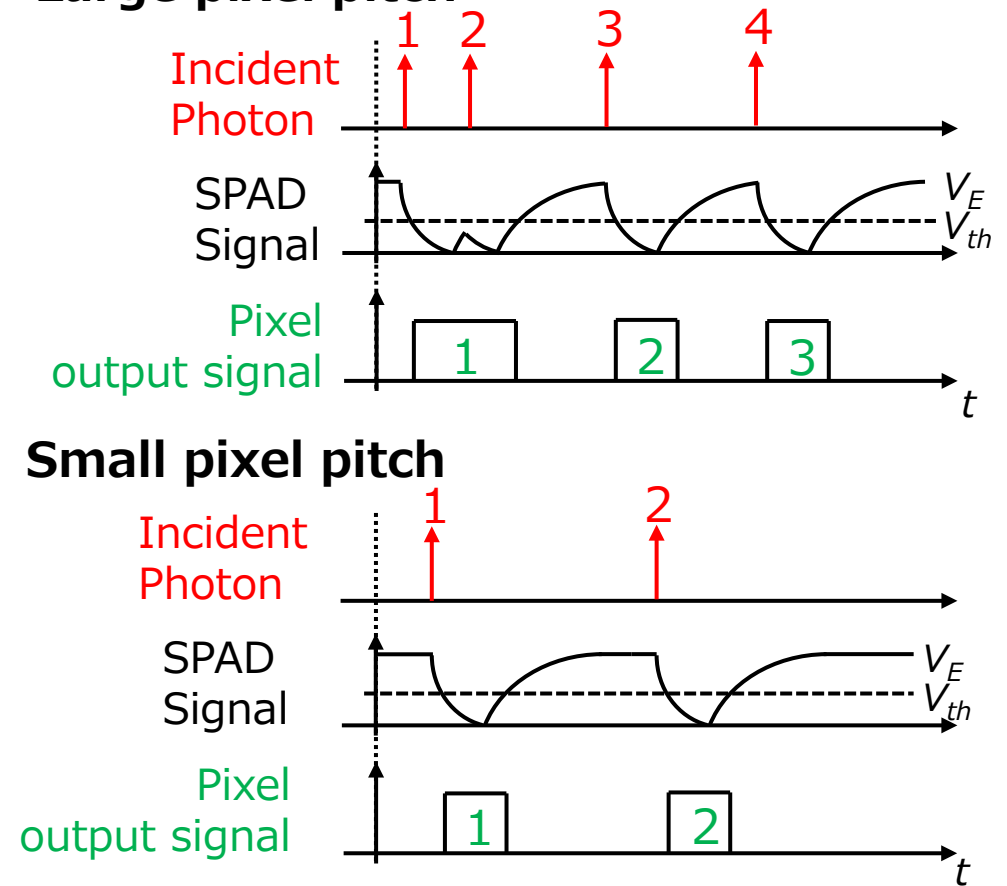
- The SPAD pixel size has been reduced to improve the SPAD sensors performances.
- Back-illuminated and stacked technology is mainly applied in the last 3 years.

Impact of pixel size reduction



Large pixel pitch

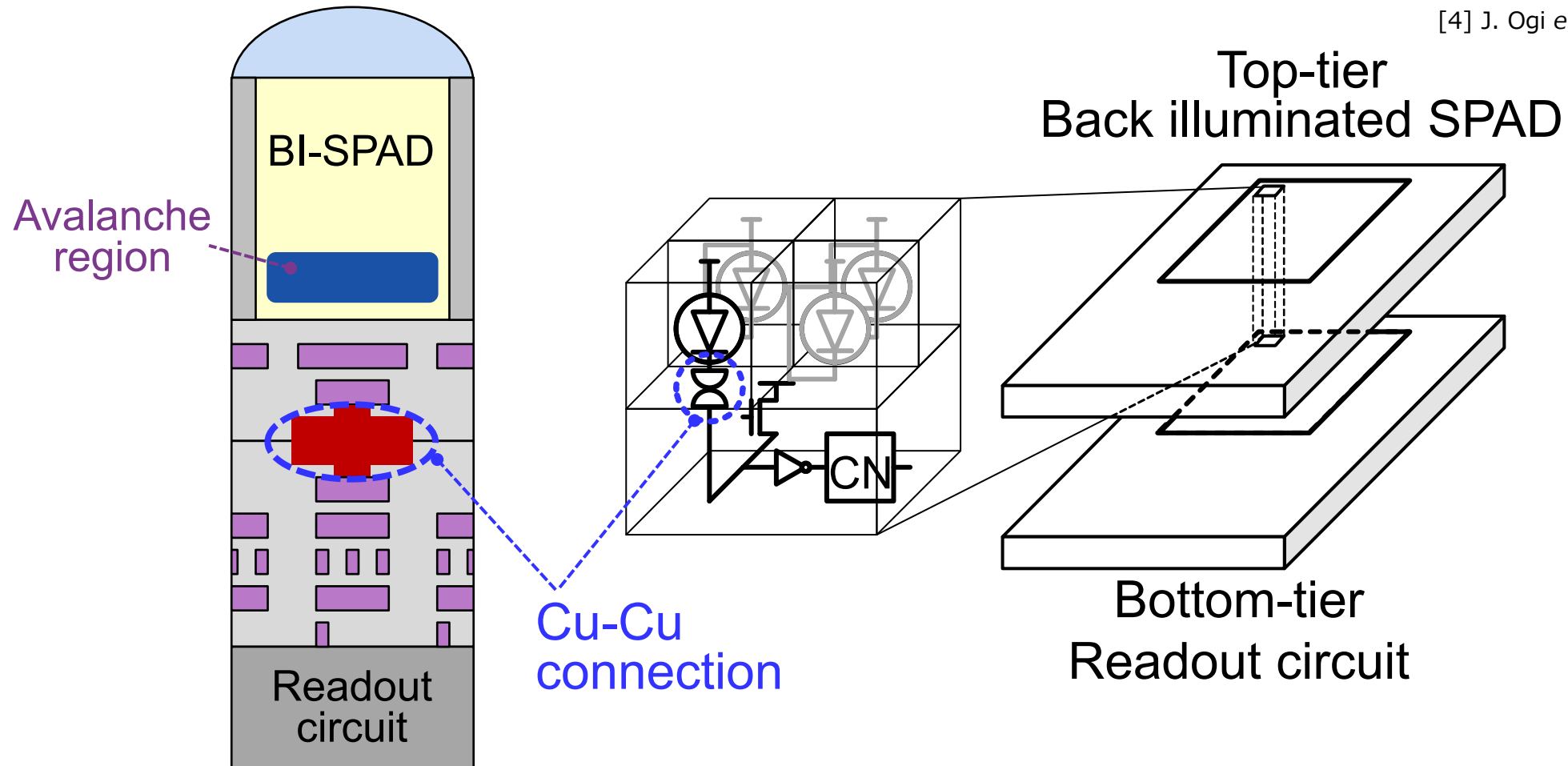
[9] S. Shimada *et al.*, IEDM 2022



- A small pixel pitch is essential to increase the resolution
- The small pixel also contributes to detect high photon flux

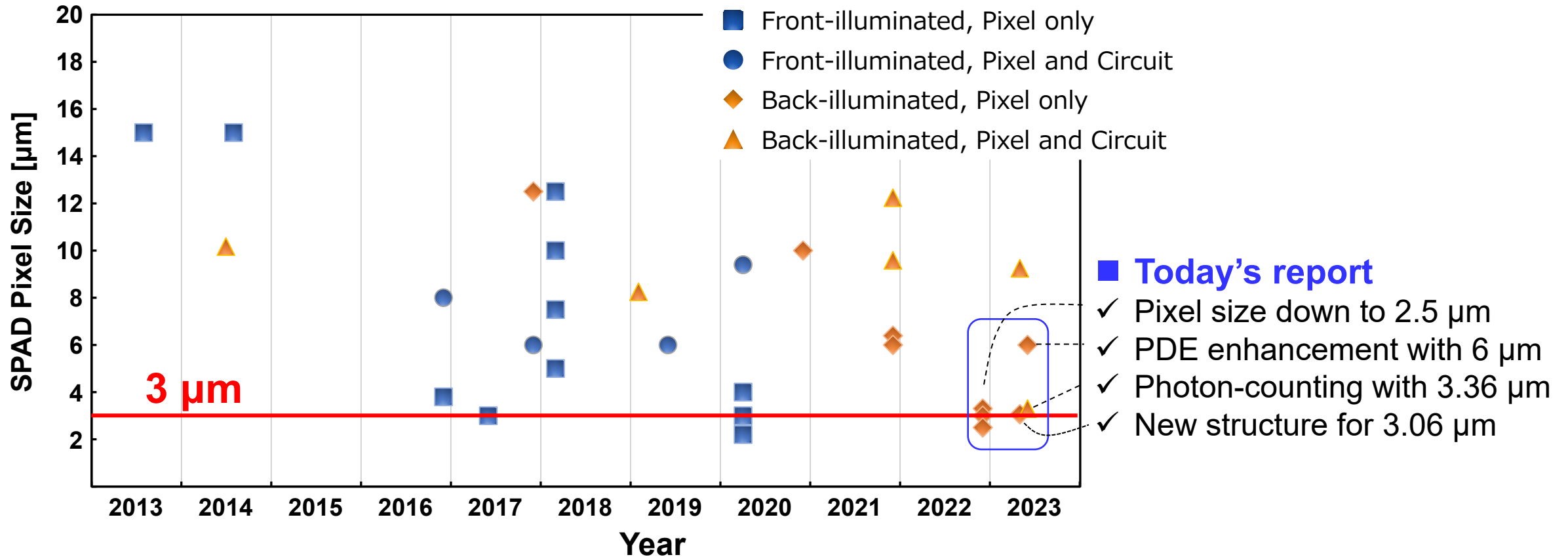
Back-illuminated SPAD stacked with pixel-front-end circuits

[4] J. Ogi *et al.*, ISSCC2021



- Back-illuminated SPAD pixel and 3D stacking of pixel-front-end circuit allows high-sensitivity and small pixel pitch.

Recent advances in the pixel size reduction

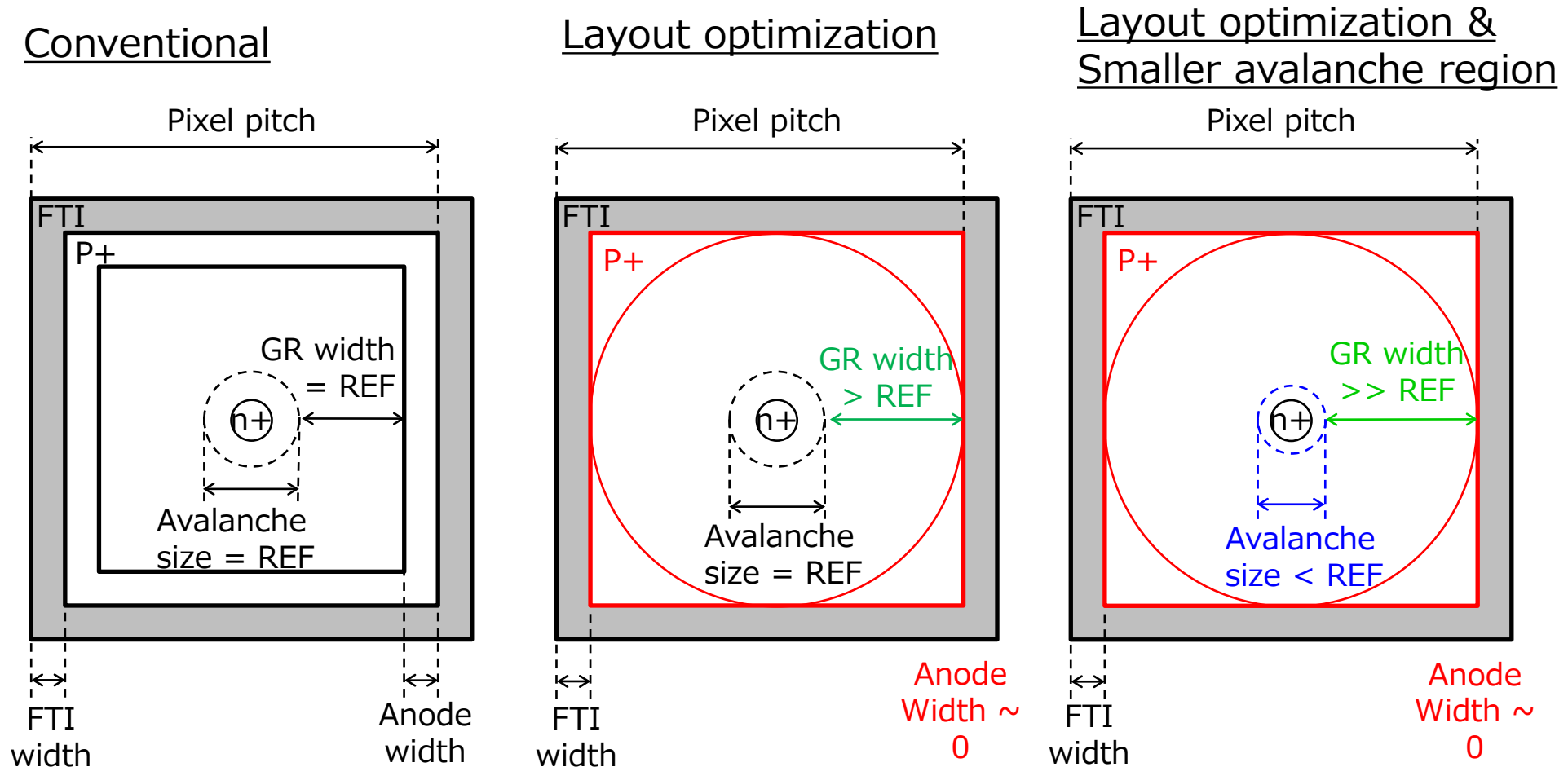


- The pixel size has been reduced less than 3 μm
- Near infrared PDE is improved with 6-μm-pitch pixel

Outline

1. Pixel size reduction in SPAD sensor development
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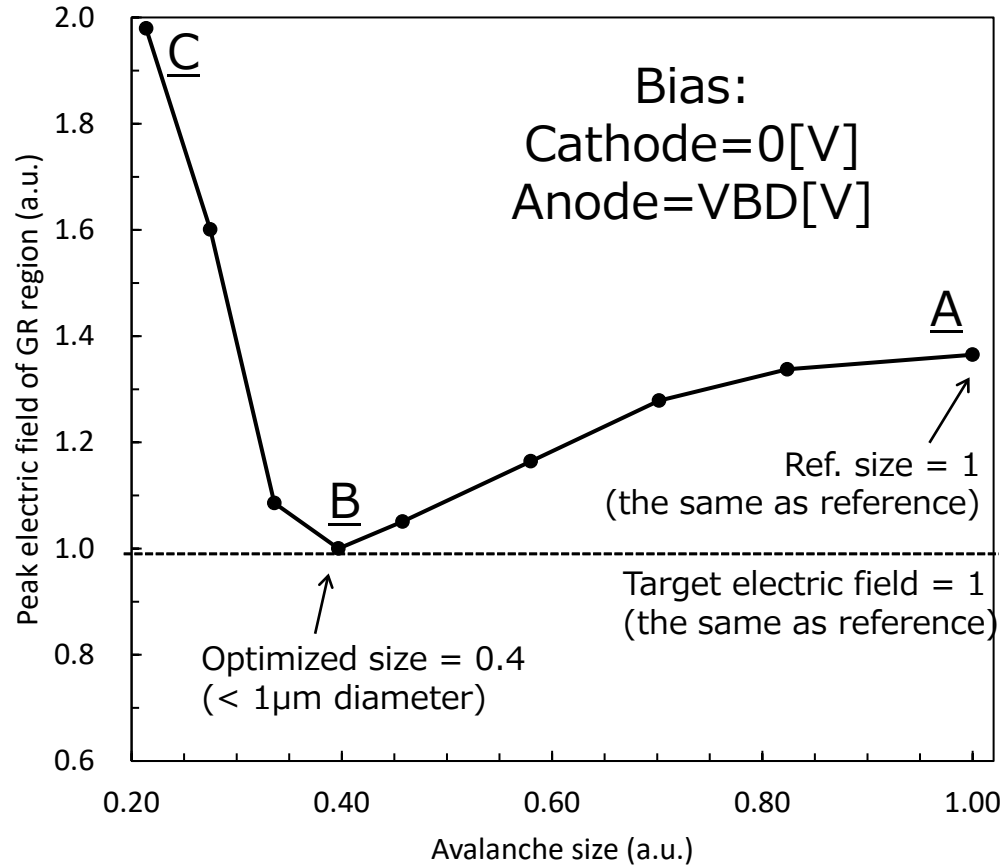
Layout optimization



- To prevent premature edge breakdown, we combined layout design optimization and smaller avalanche region to increase the GR width.

The multiplication design

3μm pixel TCAD simulation results

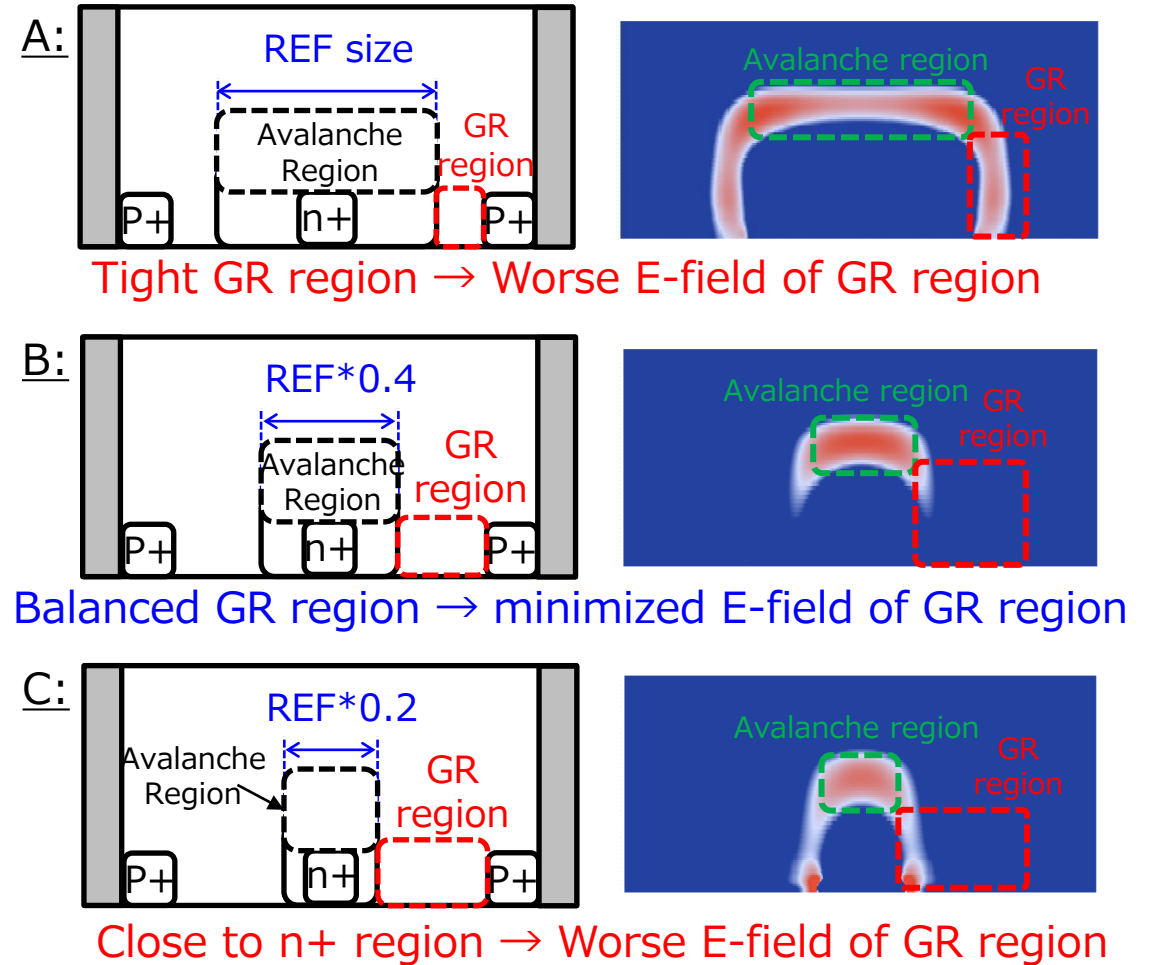


- The optimal point B was applied to avoid premature edge breakdown

Cross section Image

Electric field (simulation)

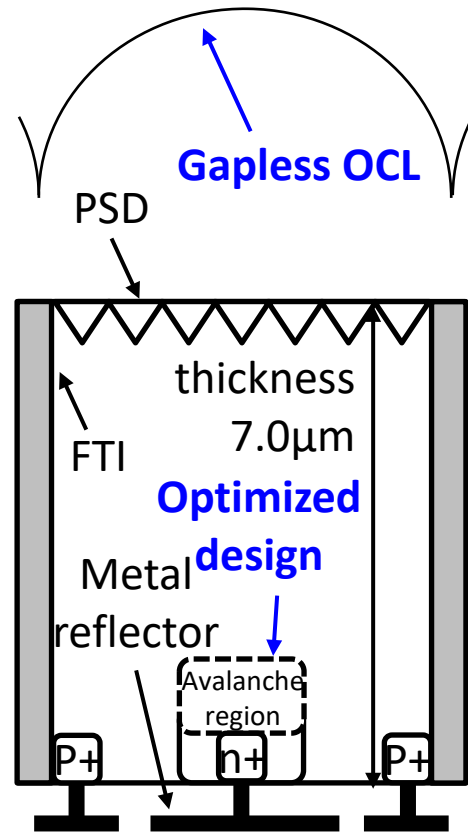
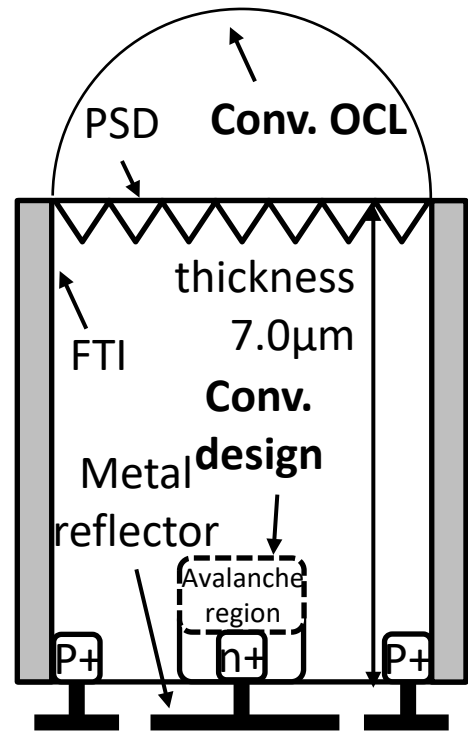
Low High



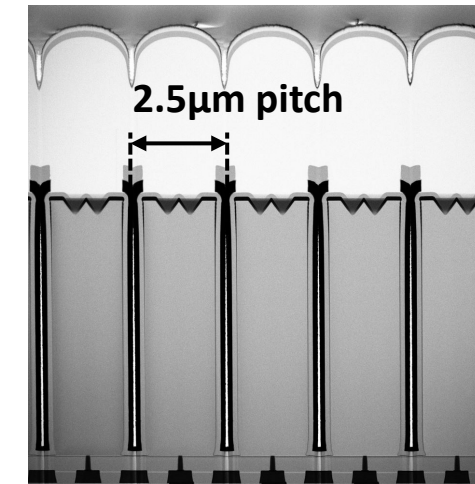
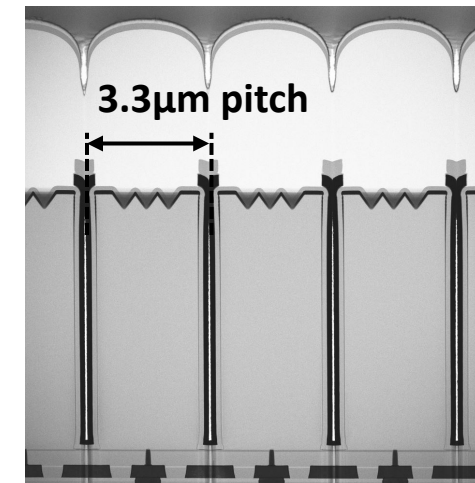
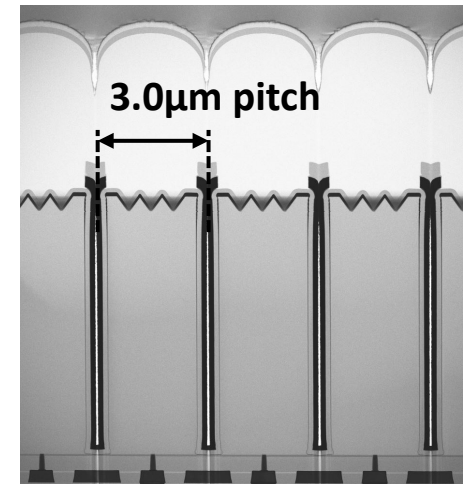
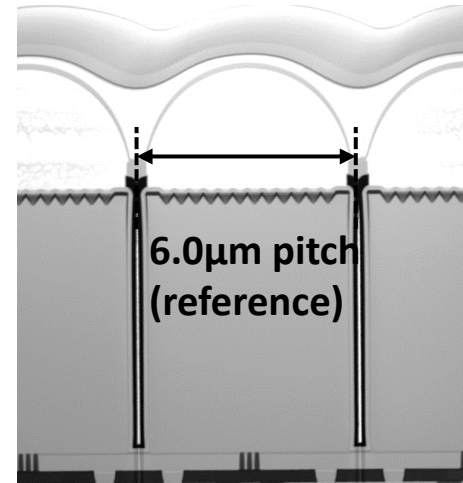
SPAD pixel structures

Reference pixel

Developed pixel

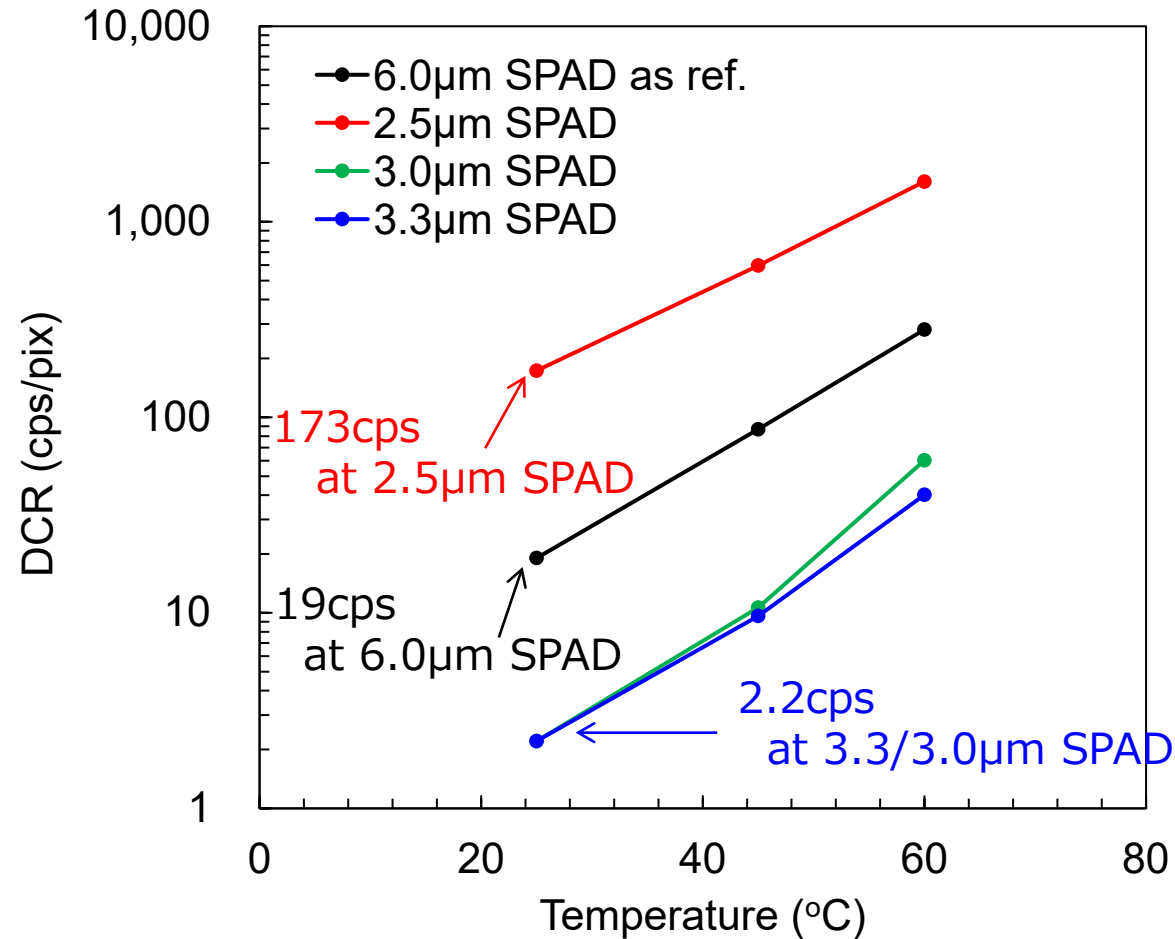


Anode Cathode Anode Anode Cathode Anode



- Cross-section of the scaled down pixels with optimized avalanche region, and Gapless OCL for PDE enhancement.

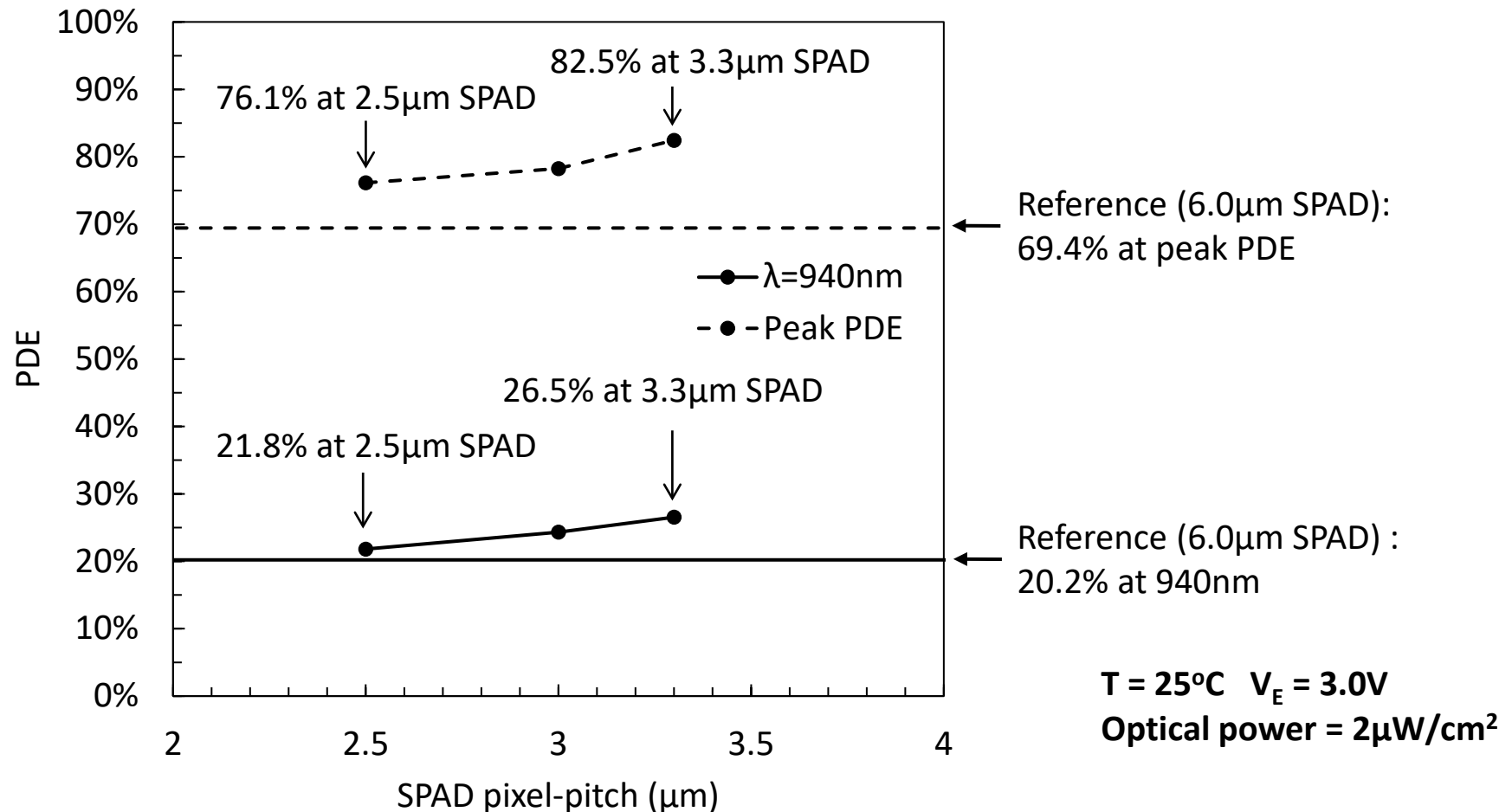
Dark count rate



$V_E = 3.0V$
Median DCR within die

- 3.3, 3.0µm pixels DCR improvement over the 6µm pixel is attributed to the avalanche region design optimization.

PDE as function of pixel pitch



- The scaled down pixels achieve higher PDE than the 6μm reference in terms of both, NIR and Peak PDE in the visible region.

Outline

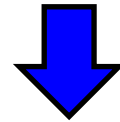
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PDE enhancement with dual diffraction structure

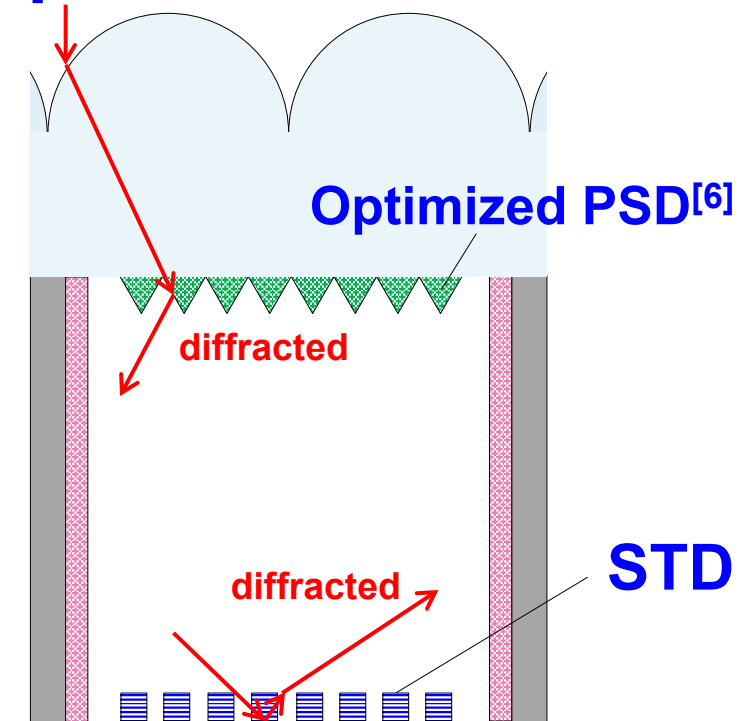
1. pyramid surface for diffraction (PSD) on incident surface
2. shallow trench for diffraction (STD) on opposite surface

PSD
+
STD

} Dual Diffraction Structure

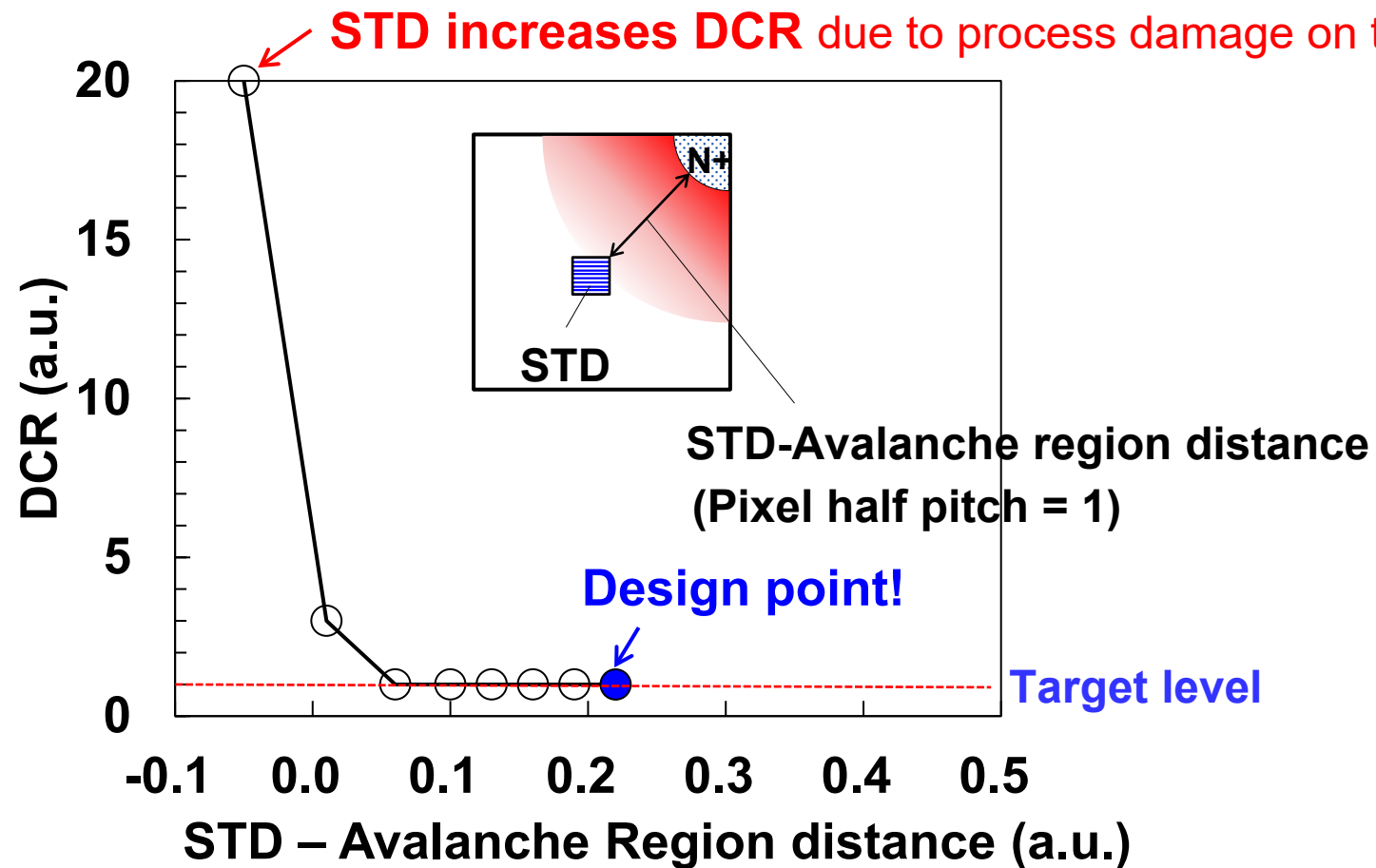


Optical path is longer than PSD only!

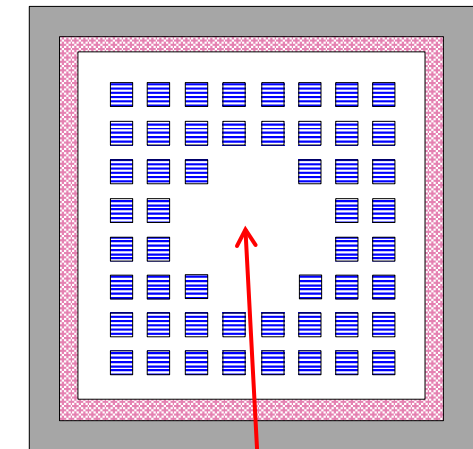


- Dual diffraction structure increase optical path in the pixel.

Shallow Trench for Diffraction (STD)



Top view of STD design



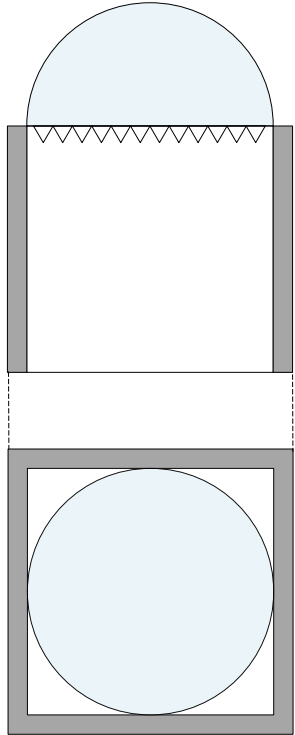
Avoid avalanche region

- Shallow trench diffraction is used for the diffraction structure on the front-side of the pixel and the design is optimized to reduce DCR.

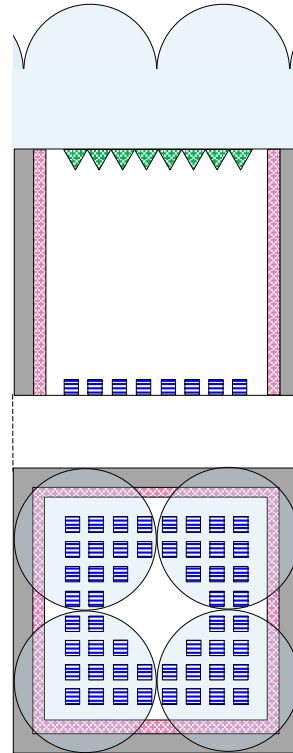
2x2 On-Chip Lens

Simulation

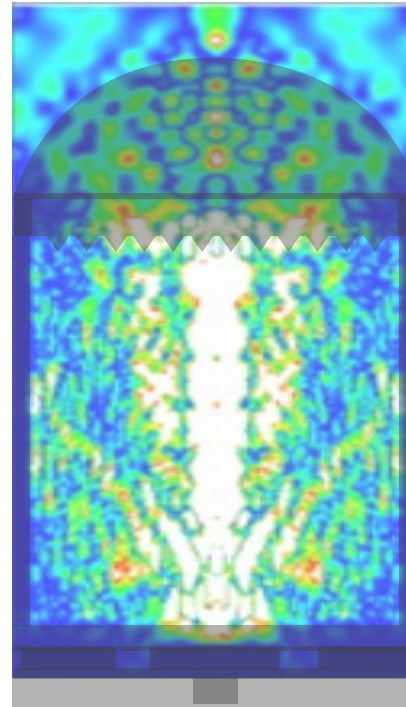
Conventional



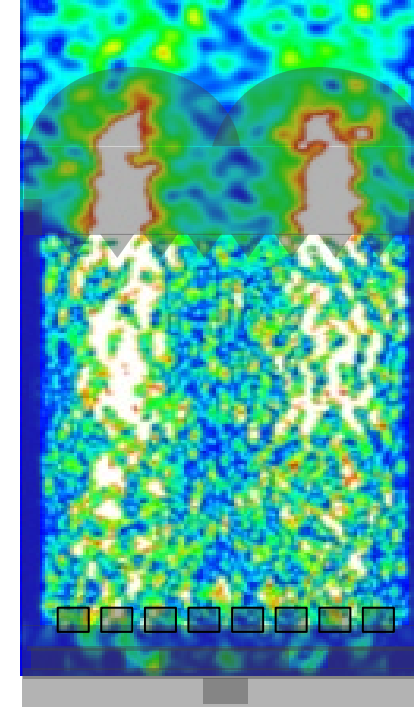
2x2 OCL



Conventional



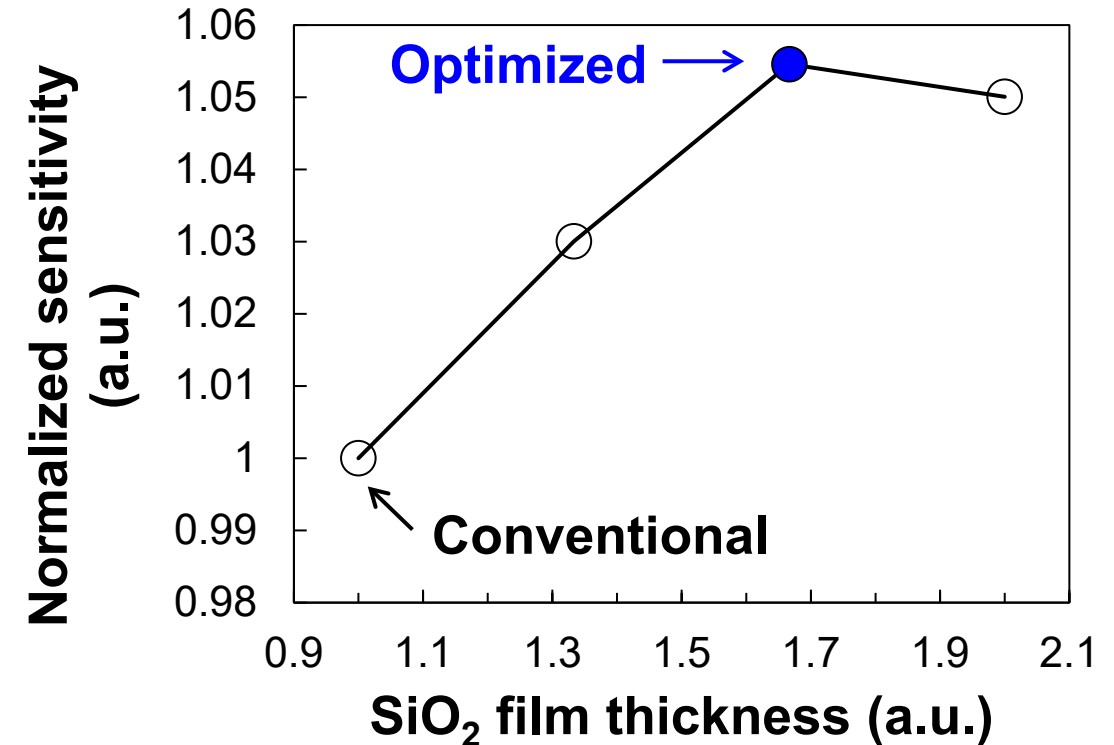
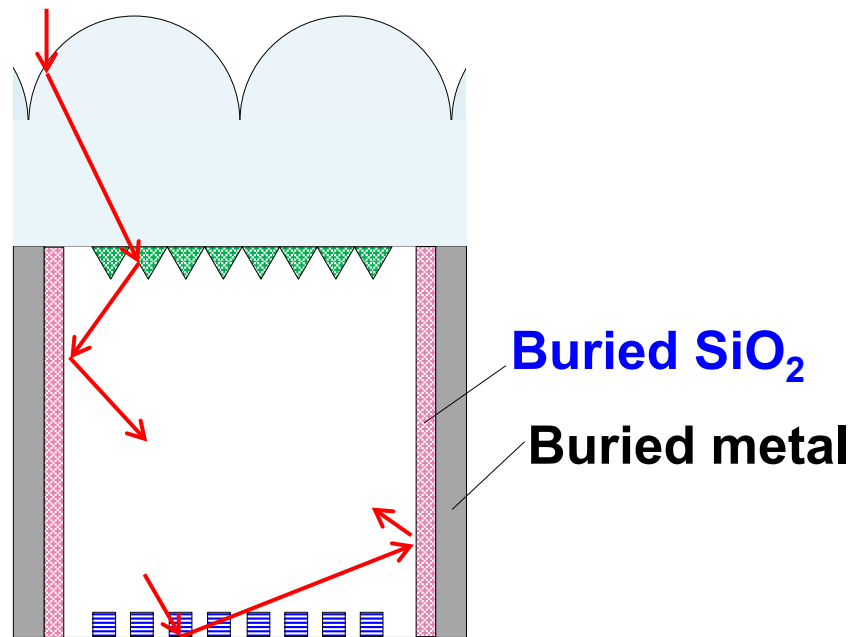
This work



**Scattering
sufficiently!**

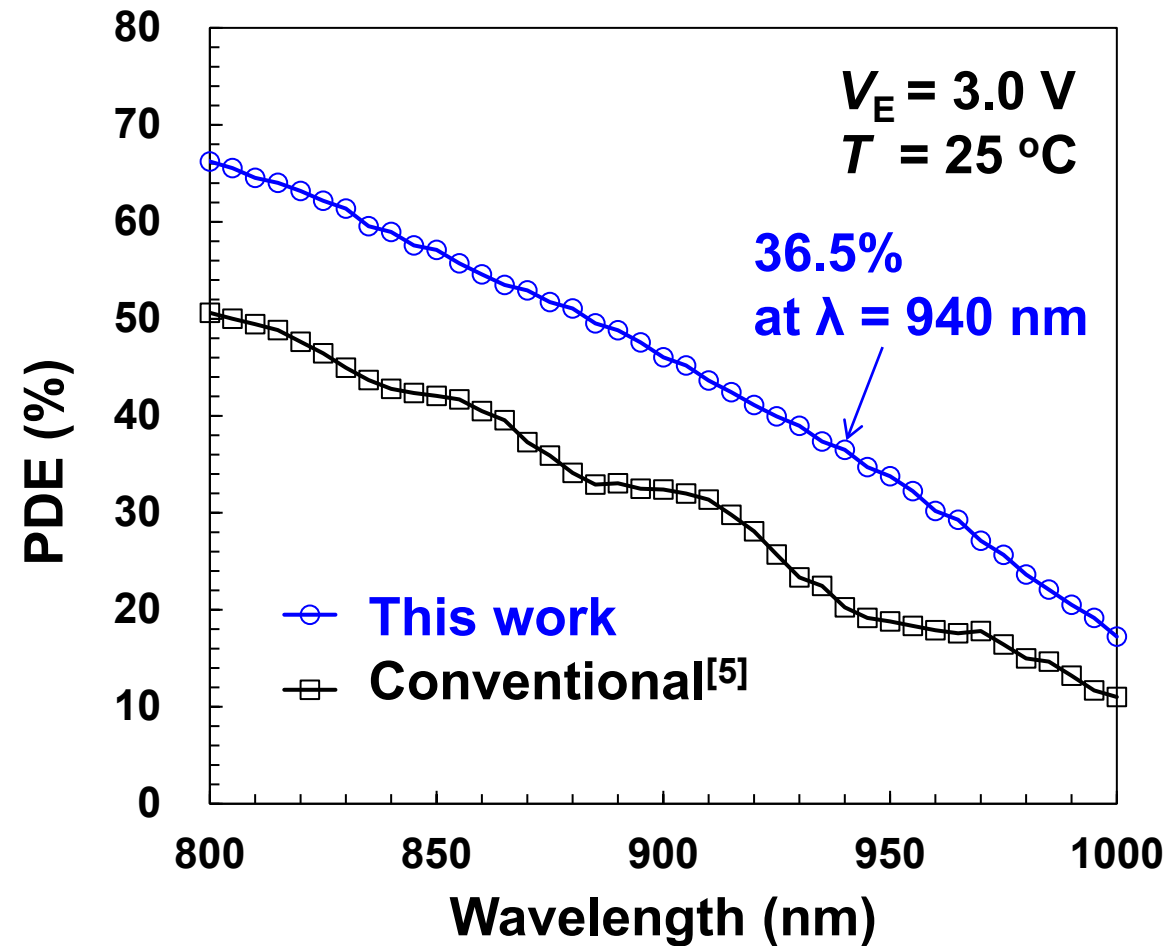
- Single OCL cannot focus on the STD.
- 2x2 OCL per pixel is used to increase the scattering effect.

Full Trench Isolation (FTI) optimization



- Metal buried FTI, which blocks cross-talk, degrades PDE due to light absorption on the metal.
- The buried SiO₂ thickness is optimized to reduce the absorption.

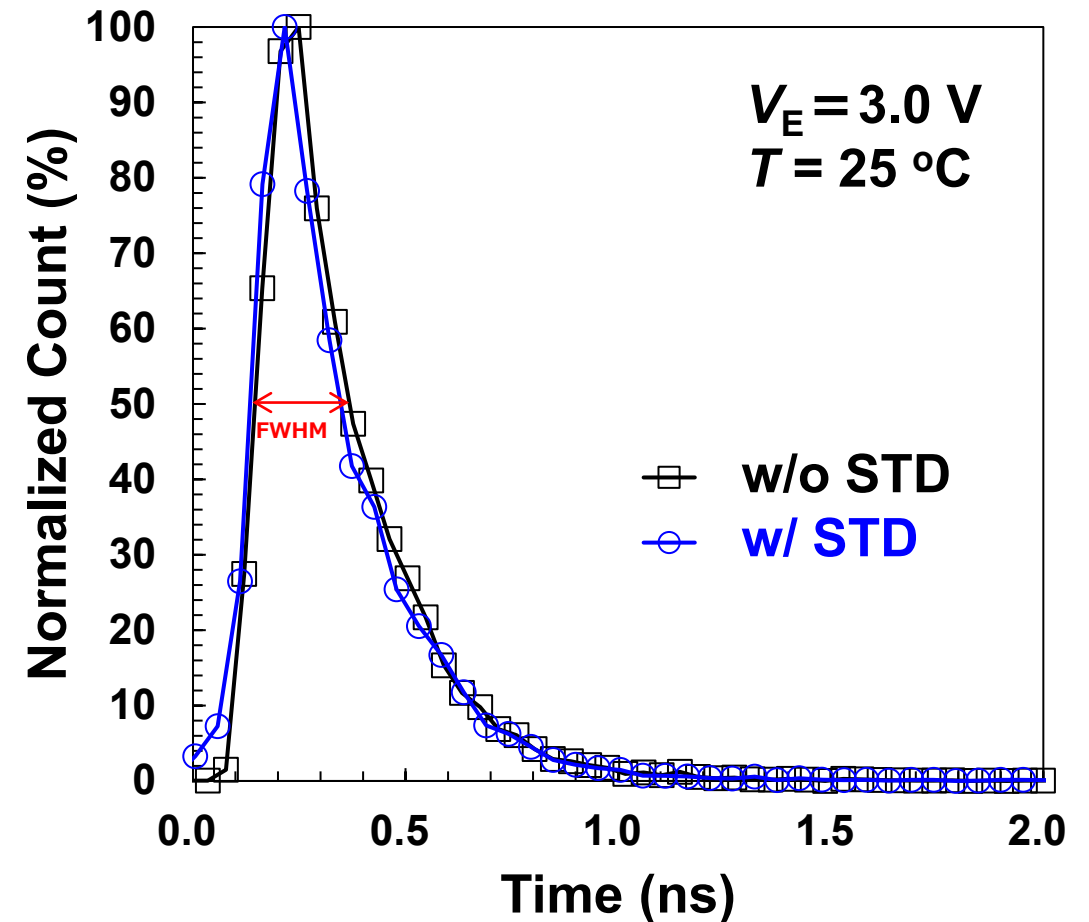
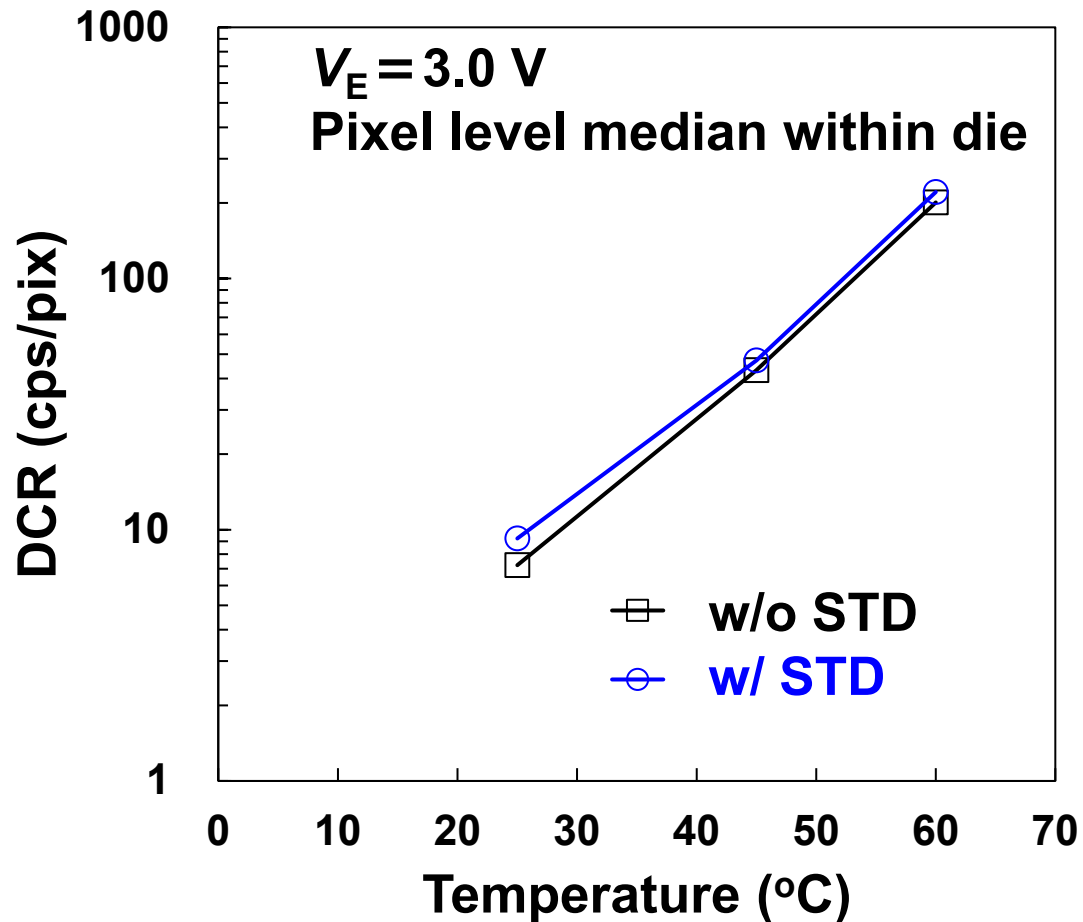
PDE for near infrared



**>16 point increase
at $\lambda = 940 \text{ nm}$**

- PDE of 36.5 % at 940nm wavelength is achieved.

DCR & Timing jitter

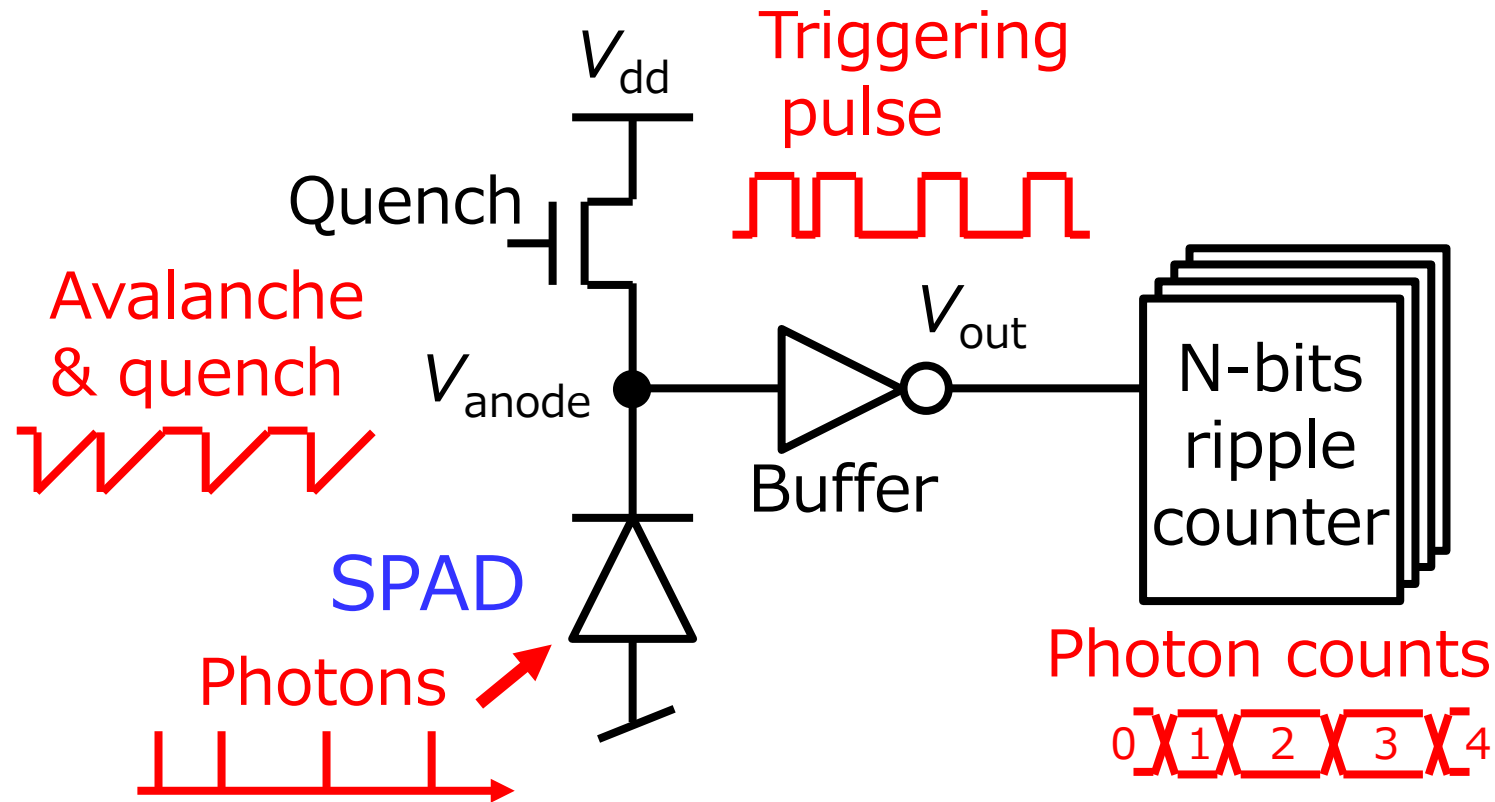


- DCR & timing jitter are maintained with STD.

Outline

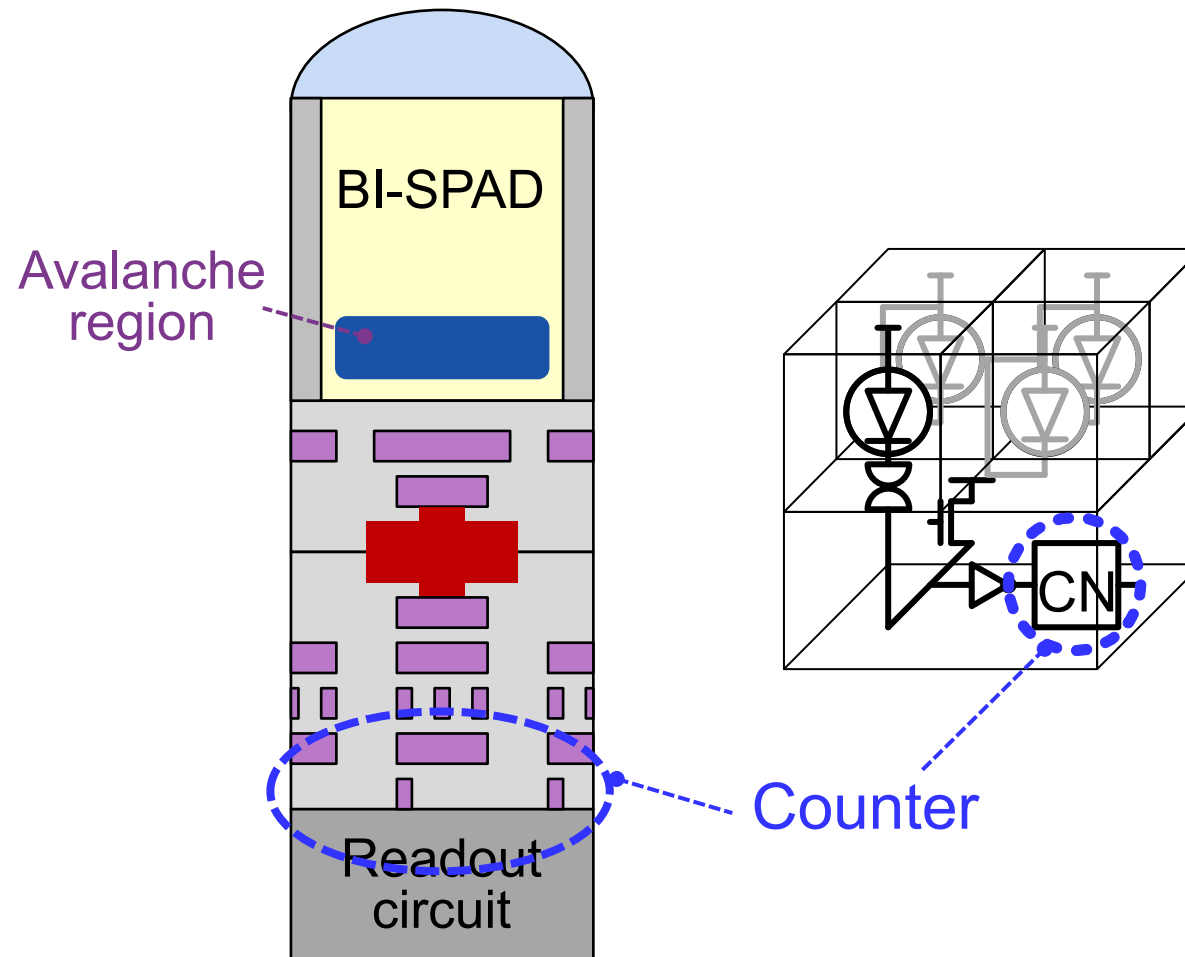
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Photon counting with SPAD



- The photons can be counted using the triggering pulse which is induced by incident photons in the SPAD.

Readout circuit size reduction



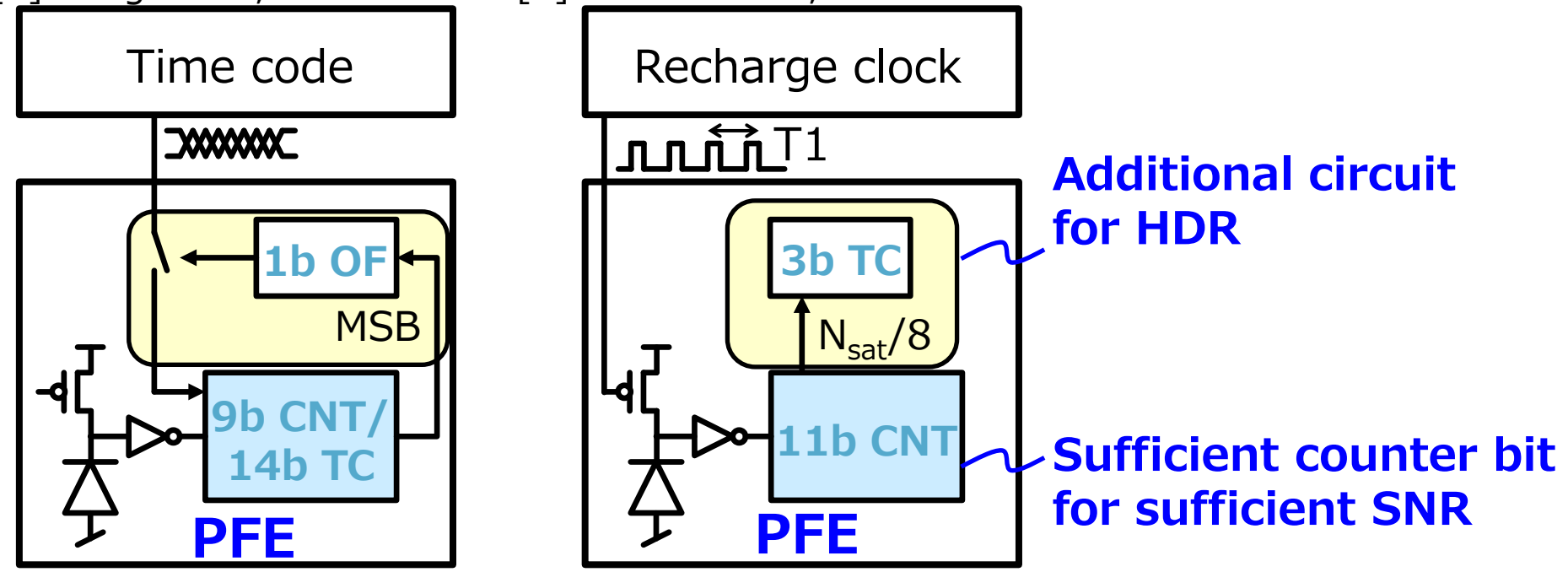
- The counter size must be reduced for the pixel pitch shrinking

Challenges in reducing pixel size

Previous works

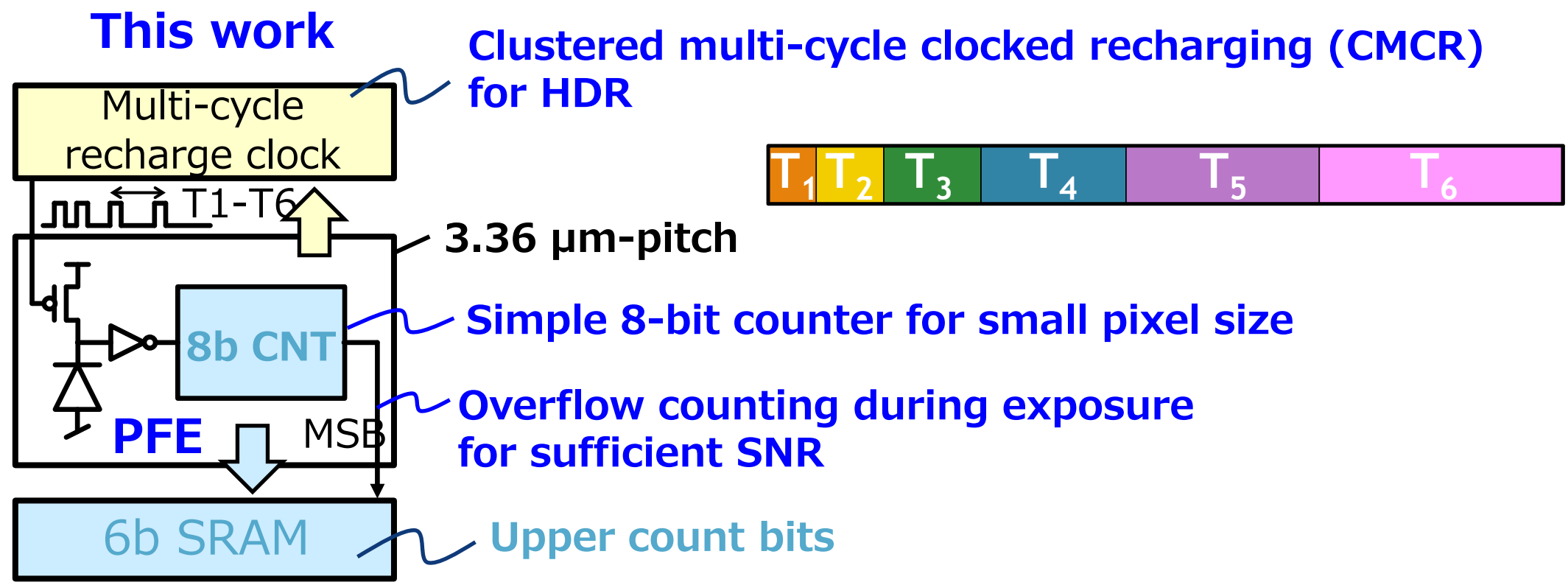
[4] J. Ogi *et al.*, ISSCC2021

[6] Y. Ohta *et al.*, ISSCC2022



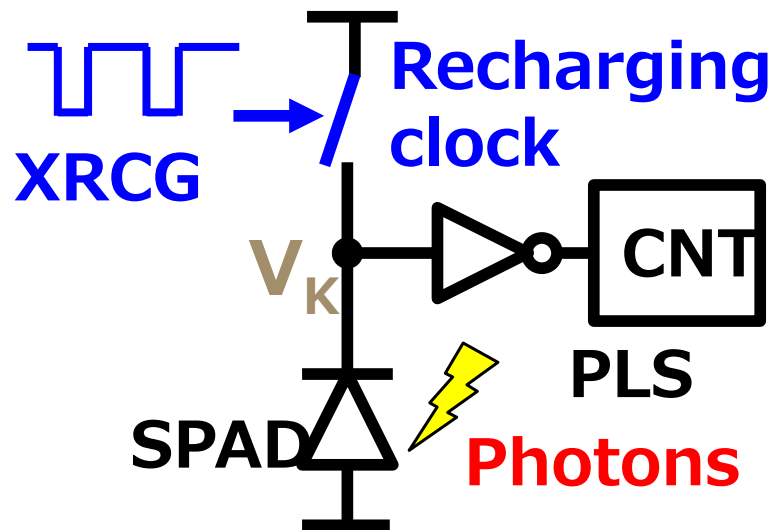
- Additional circuits for HDR and sufficient counter bits for sufficient SNR are needed in pixel front-end (PFE) circuit.

Approach to 3.36 μm -pitch pixel circuit

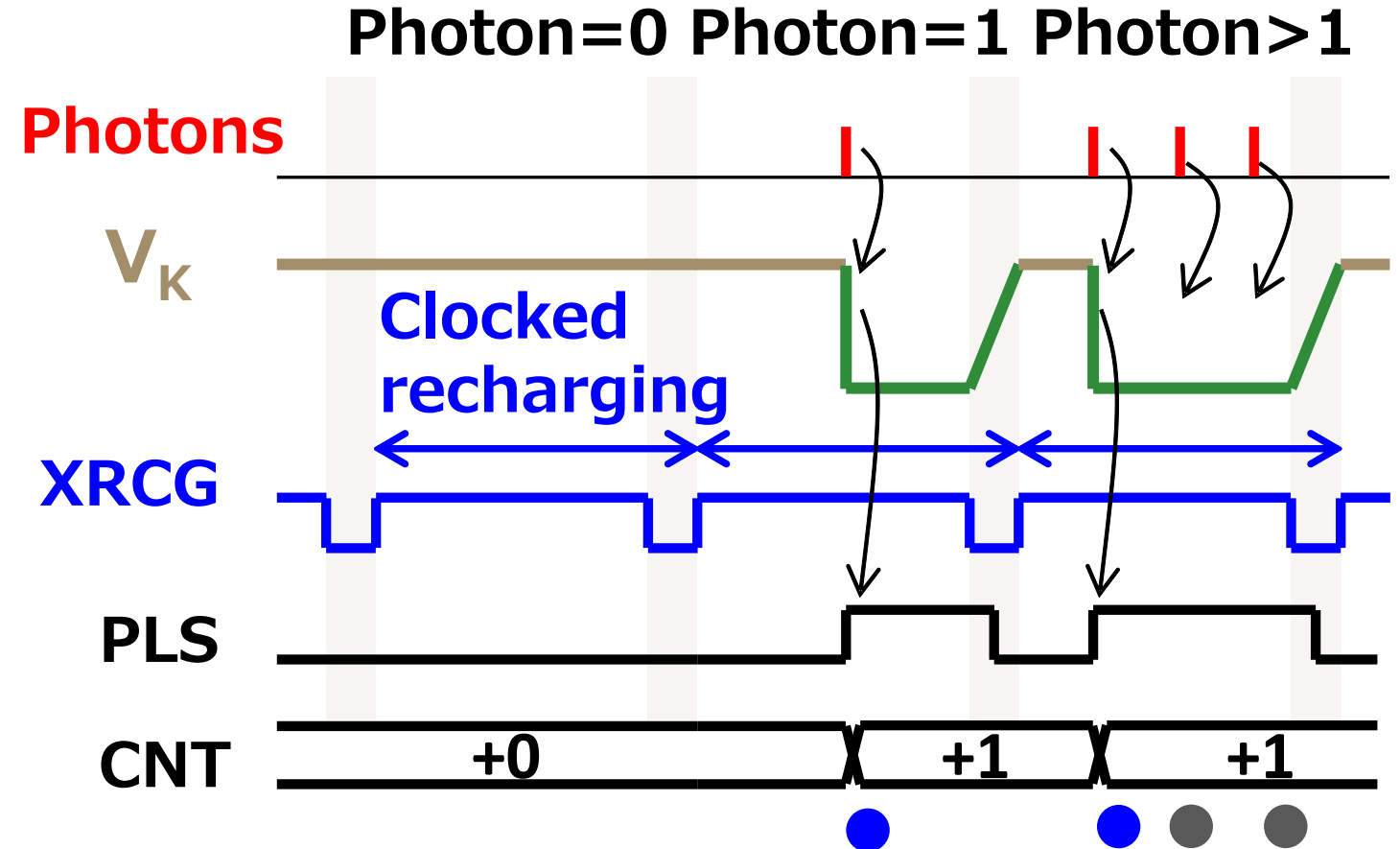


- 3.36 μm -pitch pixel circuits is realized by moving the HDR circuit and upper count bits to outside of the PFE.

Photon-counting with clocked recharging



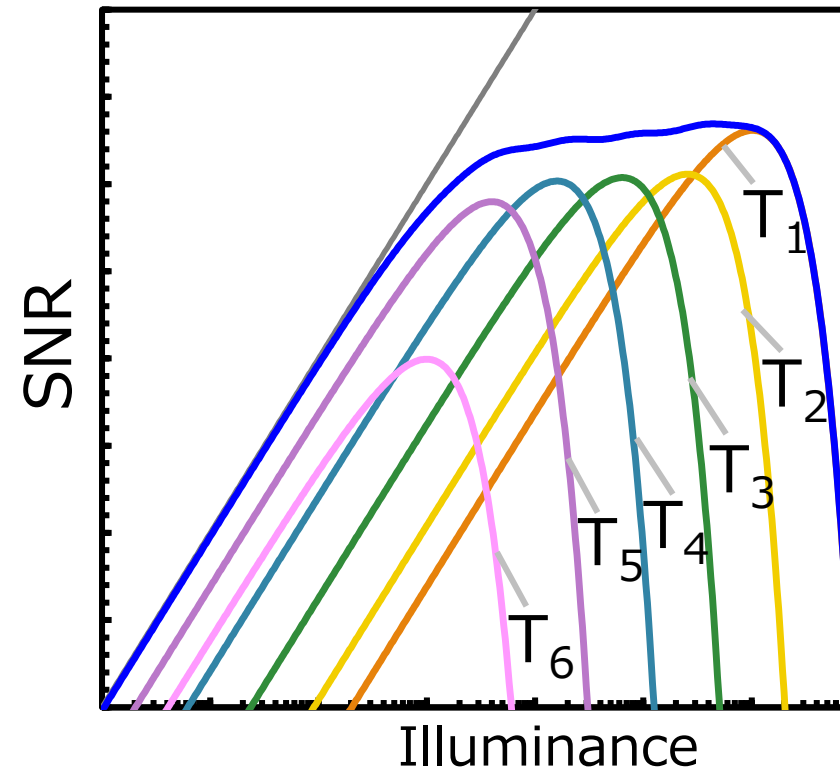
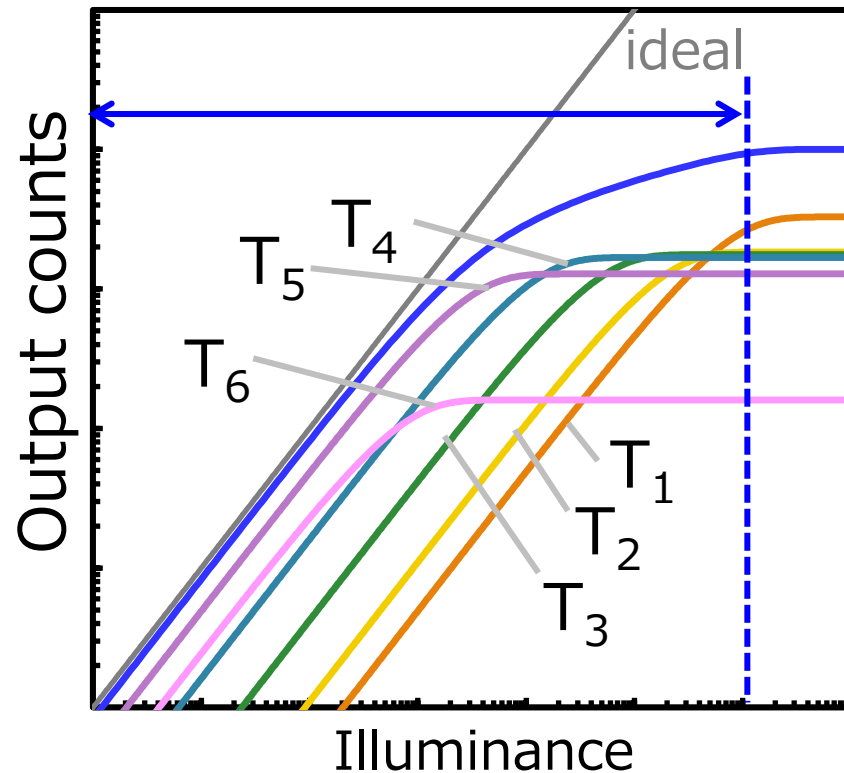
[5] Y. Ota *et al.*, ISSCC 2022



- Number of time slots wherein photons are incident once or more is counted.

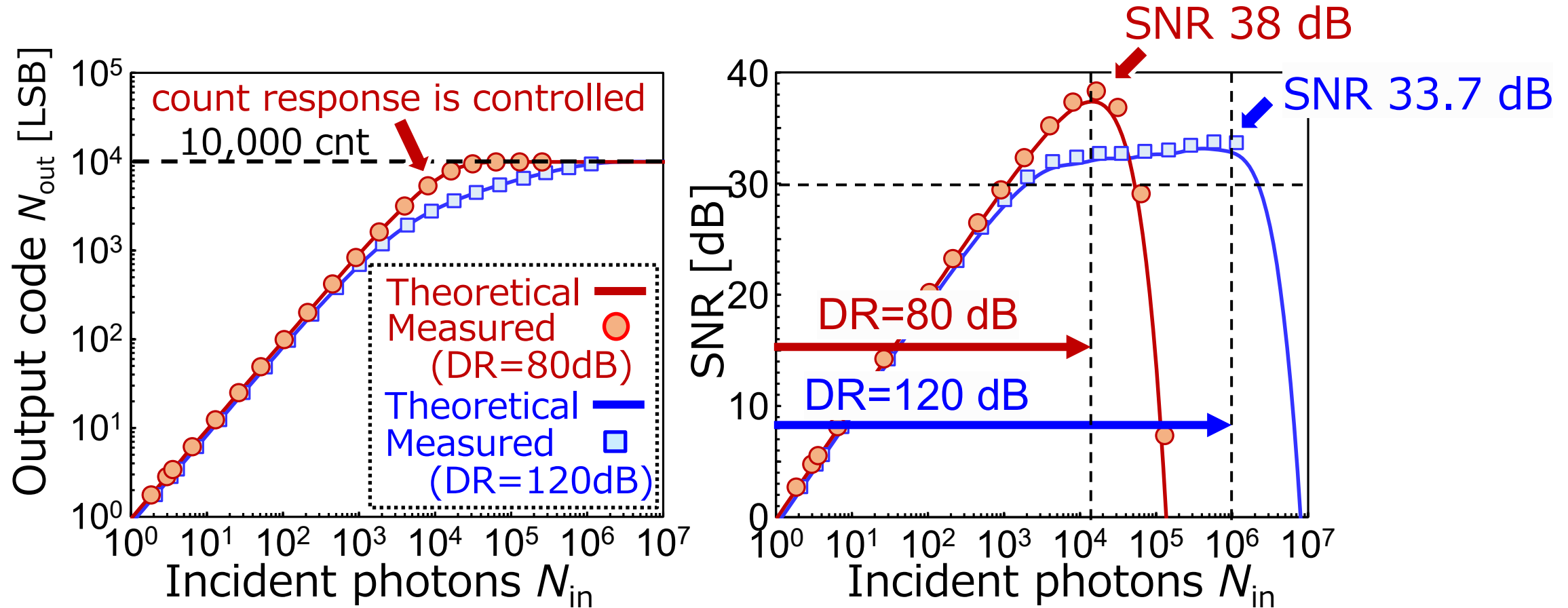
Multi-cycle clocked recharging

Multi-cycle
Six cycles combination



- Six different time cycles are combined to achieve 120 dB DR and monotonic increase of SNR (no SNR dip)

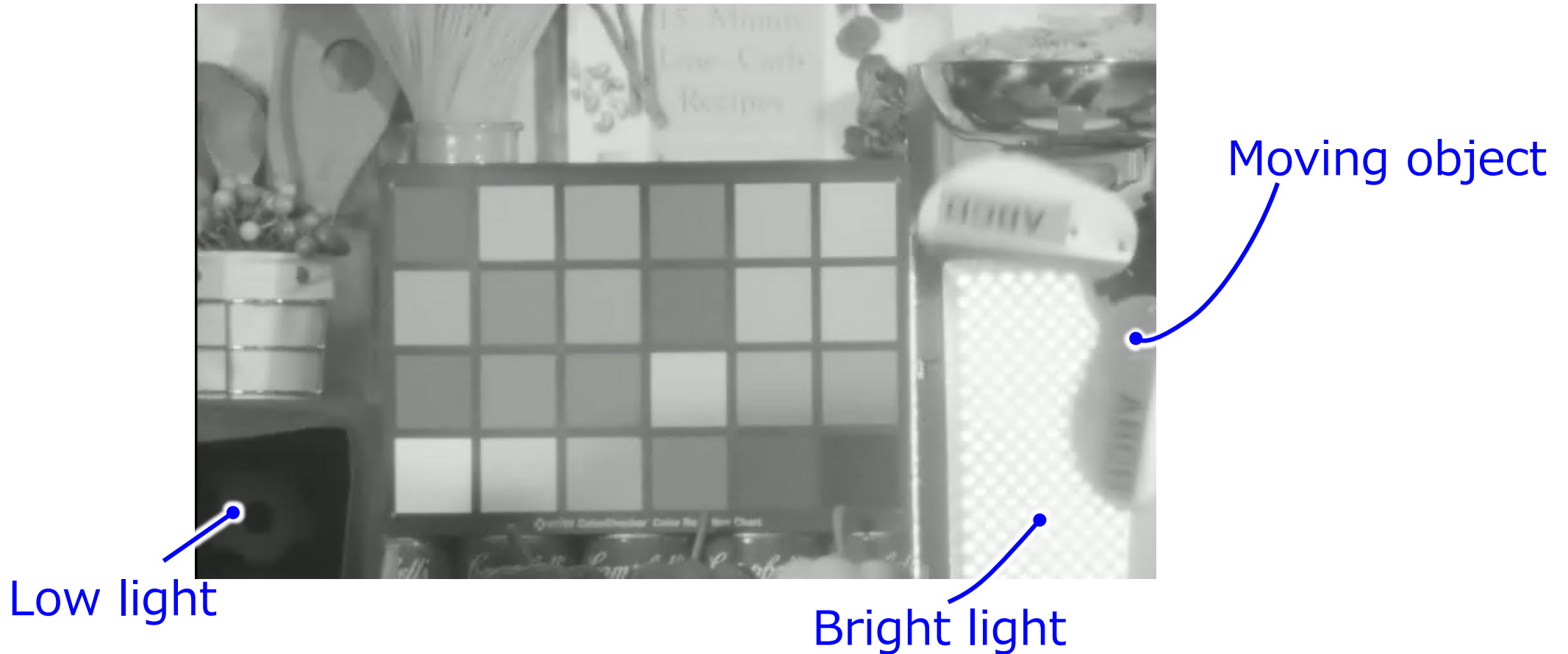
SNR and DR control



- 120 dB DR is achieved with the multi-cycle clocked recharging.
- The blight-light response can be controlled with the clock setting.

HDR image capturing

Exposure $1/150$ s, Framerate 150 fps



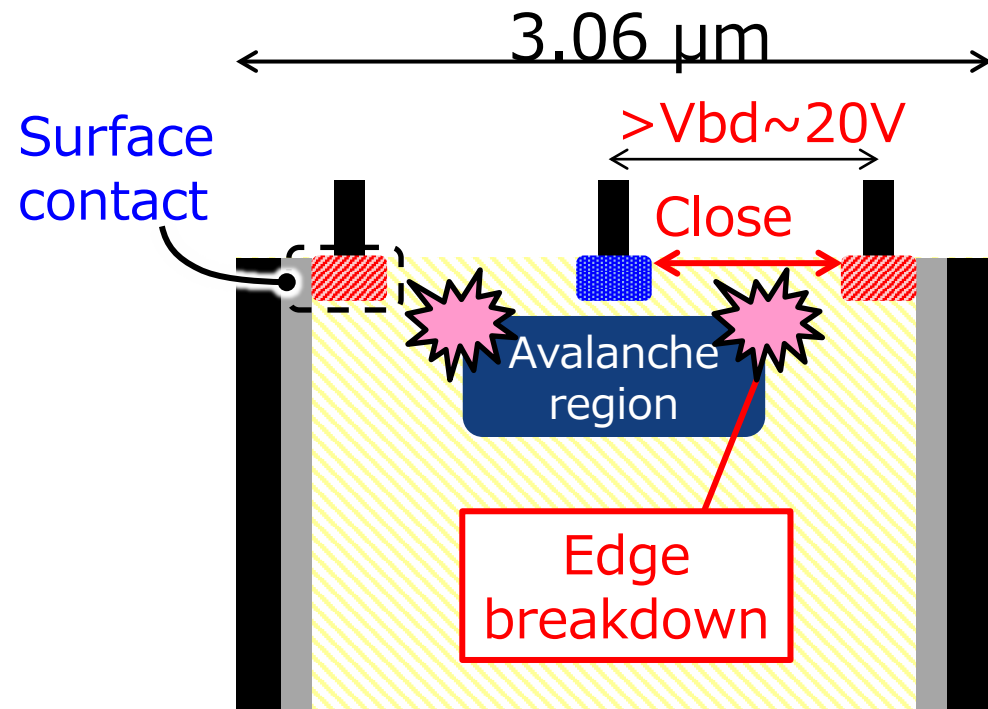
- Global shutter movie with 120 dB DR and 150 fps is demonstrated.

Outline

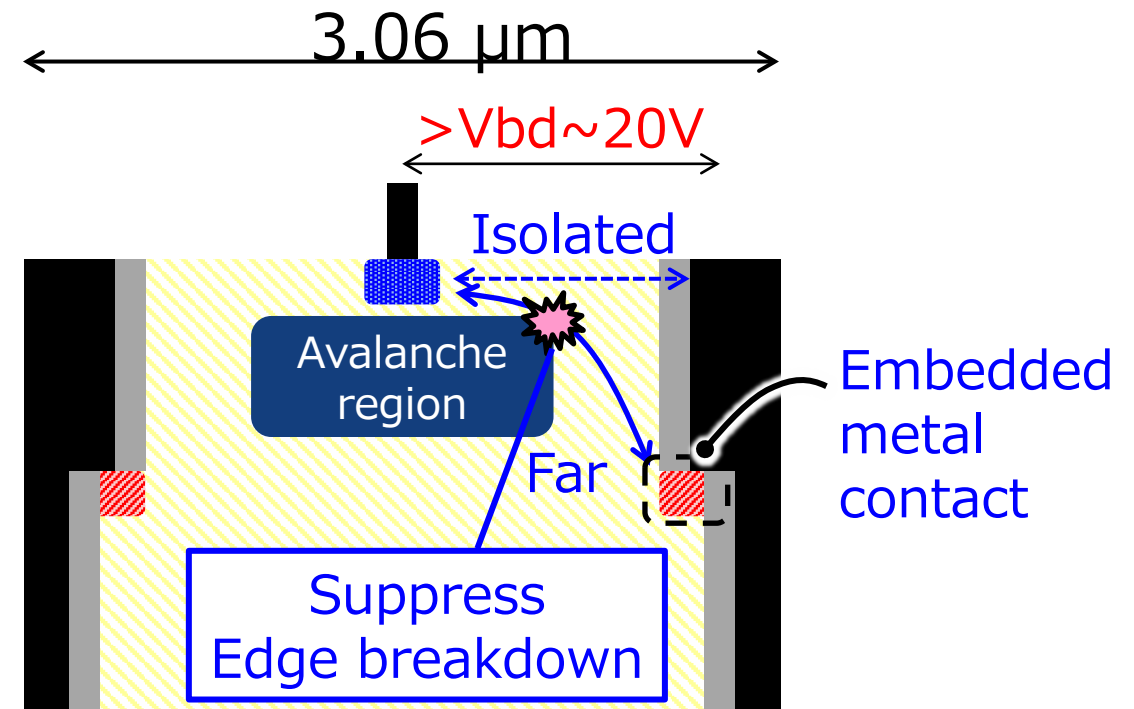
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Embedded metal contact structure

The same structure
for 6 μm or larger pixels



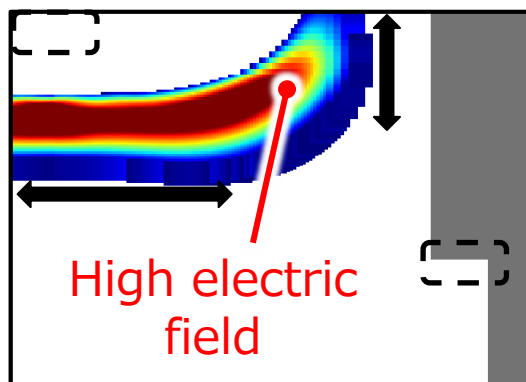
Proposed structure



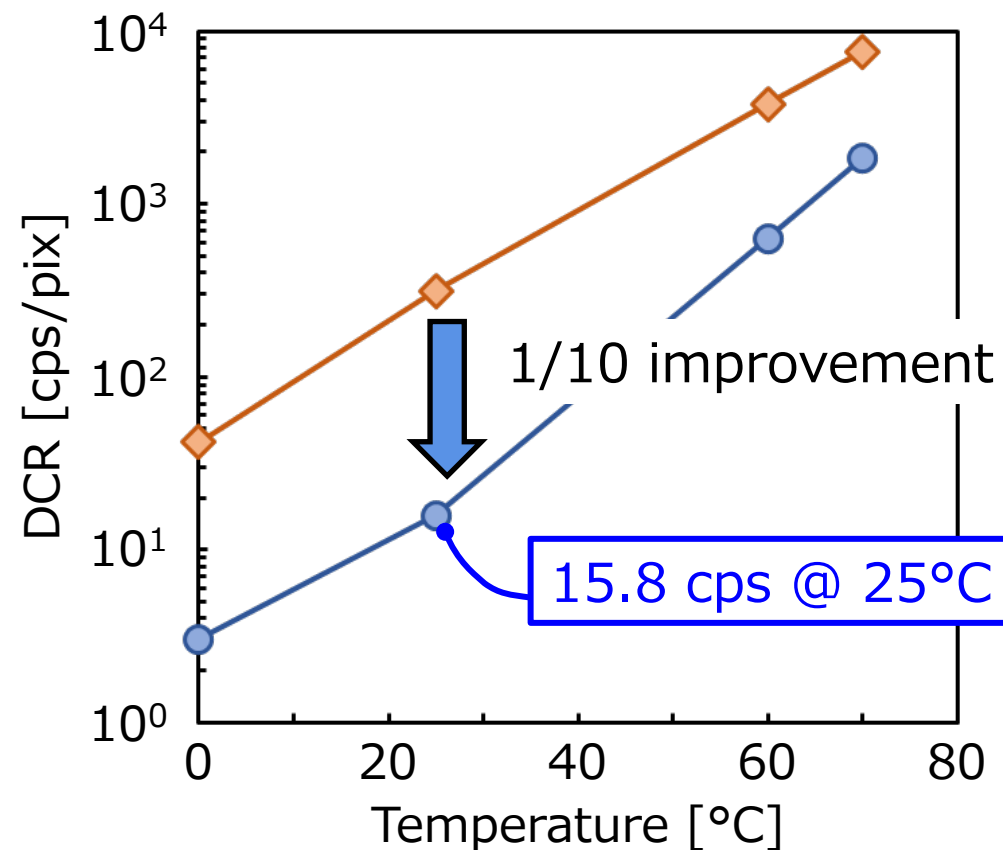
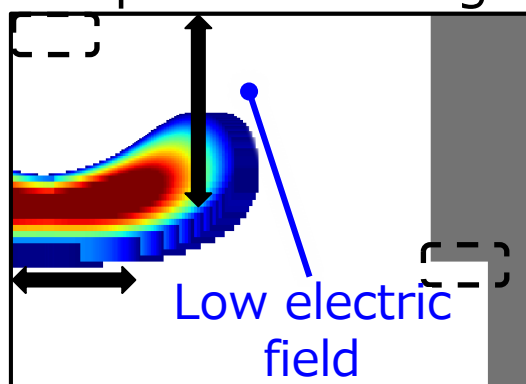
- The embedded metal contact contribute to suppress the edge breakdown by increasing distance b/w anode and cathode region.

The dark count rate

◆ Basic design

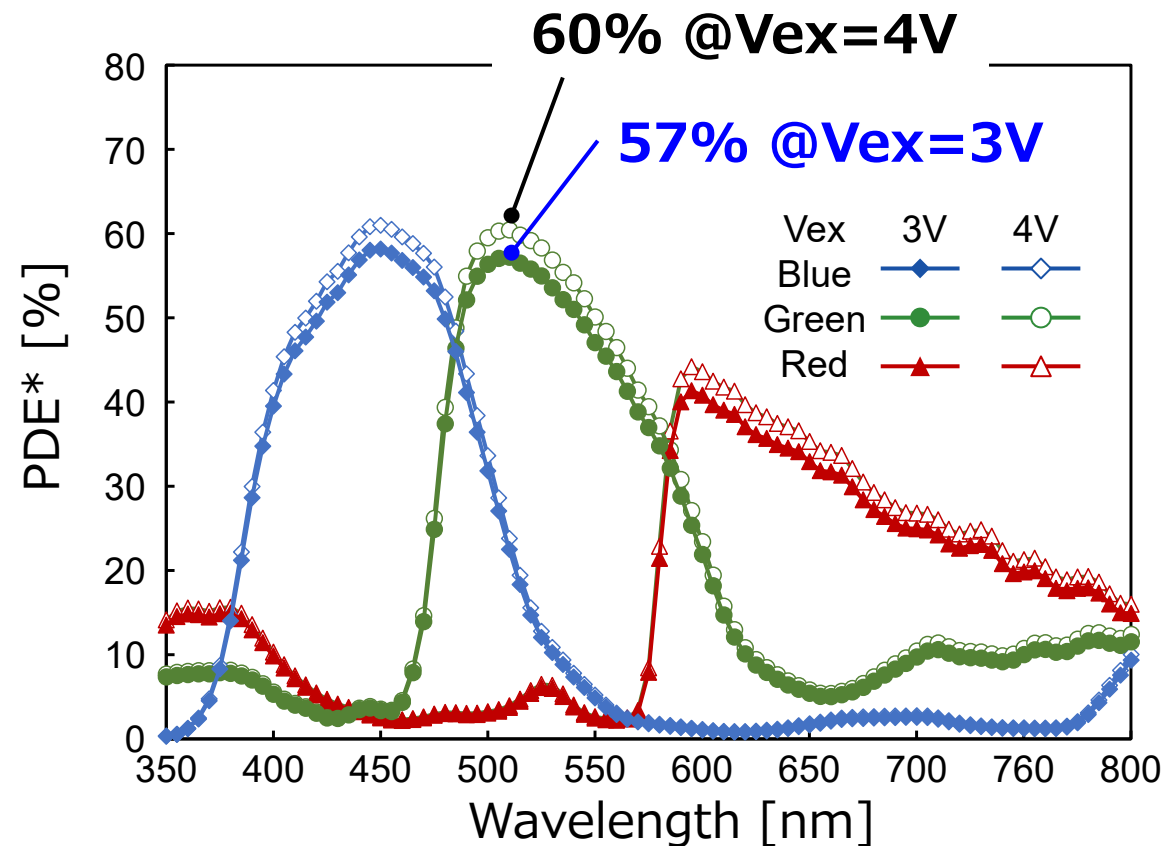


● Optimized design



- DCR is successfully reduced with the embedded metal contact and the optimized design to decrease the electric field on the pixel edge.

The photon detection efficiency



Measured at 25 °C

*Photon detection rate to incident photons on the whole pixel area (3.06 μm^2)

- The PDE is 57% even with the small pixel size because of the optimized potential slope for the electron transfer.

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Pixel size and performances.

	Unit	IEDM 2016 [13]	IISW 2017 [14]	JSTQE. 2018 [15]	ISSCC 2019 [2]	Optics 2020 [16]	IEDM 2021 [17]	IISW 2023 [18]	IEDM 2020 [7]	IEDM 2021 [8]	IEDM 2022 [9]	VLSI 2023 [10]	IISW 2023 [12]	
Pixel pitch	μm	7.83	3	5	9.2	4	6.39	10.17	10	6	3.3	2.5	6.0	3.06
V _{bd}	V	12	15.8	N/D	28.5	22.1	30	18.6	20	22	19	18	22	20.9
V _{ex}	V	3	1.2	5.8 ^{*3}	2.5	6	2.5	3.5	3.0	3	3	3	3.0	3
Peak PDE	%	11.6	6 ^{*3}	12 ^{*2*3}	23	14.2	69.4	34.4 ^{*2*} ₃	53.5 ^{*1}	69.4 ^{*1}	82.5	76.1	88.4	57
PDE at 940nm	%	3.2	~1	N/D	N/D	N/D	24.4	22	14.2	20.2	22.5	20.4	36.5	N/D
DCR @25°C	cps	10974	1343	17.3 ^{*3}	20.3	2.5	1.8	8.6 ^{*3}	3	19	2.2	173	10	15.8
Jitter FWHM	ps	205	185	N/D	N/D	72	100	103	172	137	196	214	209	N/D
Cross-talk	%	N/D	<0.2 ^{*4}	4.9 ^{*3}	N/D	3.57	N/D	N/D	N/D	0.5	0.85	1.0	1.12	<0.4

- 3 - 6 μm pitch SPAD pixels have been reported with enhancement of PDE and maintaining low DCR.

Photon-counting image sensors

	Unit	Sensors2018 [19]	ISSCC2019 [2]	Optica2020 [20]	ISSCC2022 [6]	ISSCC2021 [4]	VLSI2023 [11]
Pixel pitch	μm	8.25	36.8 x 9.2	9.4	9.585	12.24	3.36
Pixel array	Pix	96 × 40	64 × 256	1024 × 1000	960 × 960	264 × 160	748 × 448
CMOS Technology	Nm	40	Stacked 90 / 40	180	Stacked 90 / 40	Stacked 90 / 40	Stacked 90 / 22
In-pixel counter	Bit	12	28	1	11+3bit latch	9	8
Max. frame rate	fps	60	30	0.45	90	250	150
Dynamic range	dB	109	129	108.1	143	124	120
SNR Max.	dB	~40	>40	30.5	33	40	33.7
SNR dipped	-	30	No dip	29.5	24	No dip	No dip
Motion artifact Suppression	N/A	No	Yes	No	No	Yes	Yes

- 3.36 μm pitch photon-counting image sensor has been reported with competitive characteristics.

Summary

- The SPAD pixel size has been reduced to improve the SPAD sensors performances.
- Back-illuminated and stacked technology are further reducing the pixel size.
- 3 - 6 μm pitch SPAD pixels have been reported with enhancement of PDE and maintaining low DCR.
- 940 nm PDE is improved to 36.5 % with 6- μm -pitch pixel
- 3.36 μm pitch photon-counting image sensor has been reported with competitive characteristics.
- SPAD pixel size is expected to be reduced further in the near future.

References

- [1] A. R. Ximenes *et al.*, ISSCC 2018.
- [2] R. K. Henderson *et al.*, ISSCC 2019.
- [3] O. Kumagai *et al.*, ISSCC 2021.
- [4] J. Ogi *et al.*, ISSCC 2021.
- [5] J. Ogi *et al.*, IISW 2021.
- [6] Y. Ohta *et al.*, ISSCC 2022.
- [7] K. Ito *et al.*, IEDM 2020.
- [8] S. Shimada *et al.*, IEDM2021.
- [9] S. Shimada *et al.*, IEDM2022.
- [10] Y. Fujisaki *et al.*, VLSI2023.
- [11] T. Takatsuka *et al.*, VLSI2023
- [12] J. Ogi *et al.*, IISW2023.
- [13] T. Al Abbas *et al.*, IEDM2016.
- [14] Z. You *et al.*, IISW2017.
- [15] F. Acerbi *et al.*, IEEE JSTQE 2018.
- [16] K. Morimoto *et al.*, Optics Express, 2020.
- [17] K. Morimoto *et al.*, IEDM 2021.
- [18] B. Mamdy *et al.*, IISW 2023
- [19] N.A.W. Duttion *et al.*, Sensors, 2018.
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